

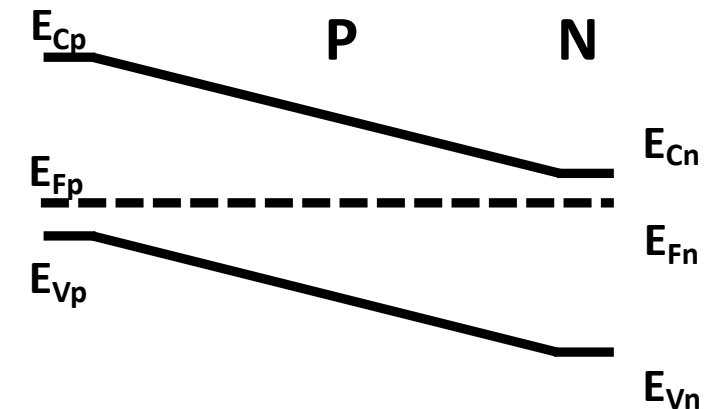
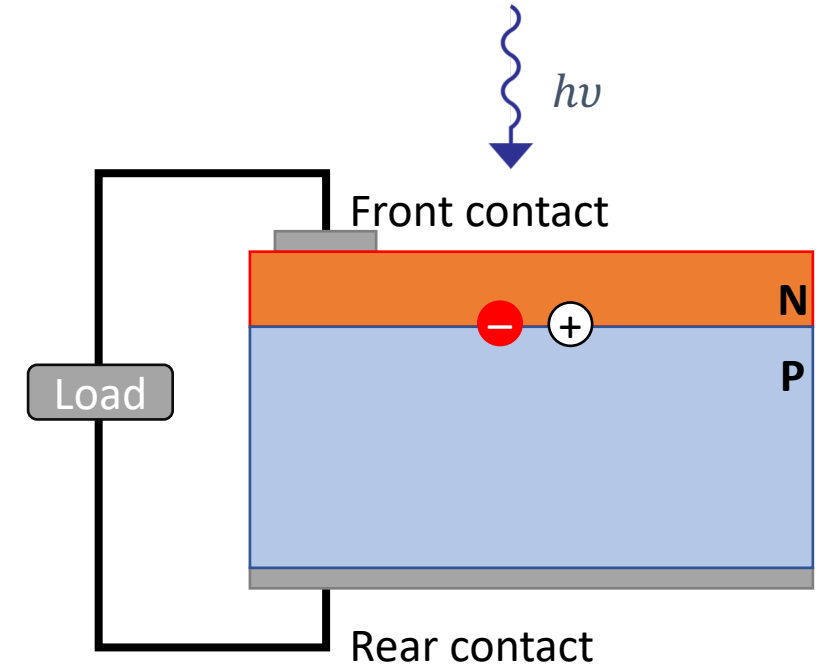
Energy Conversion by Semiconductor Devices

Jun-Ho YUM

junho.yum@epfl.ch

EPFL pn Junction Solar Cell

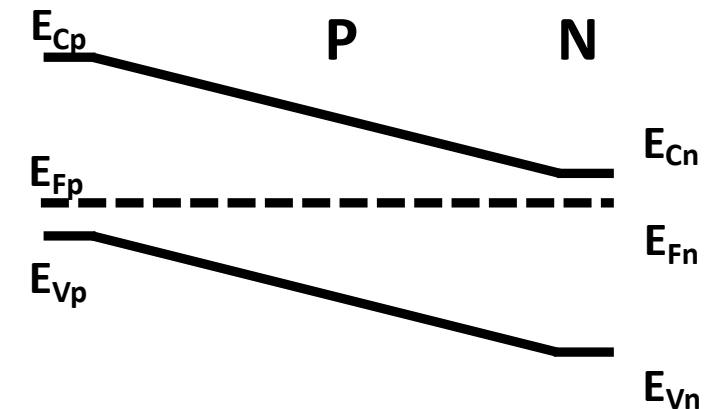
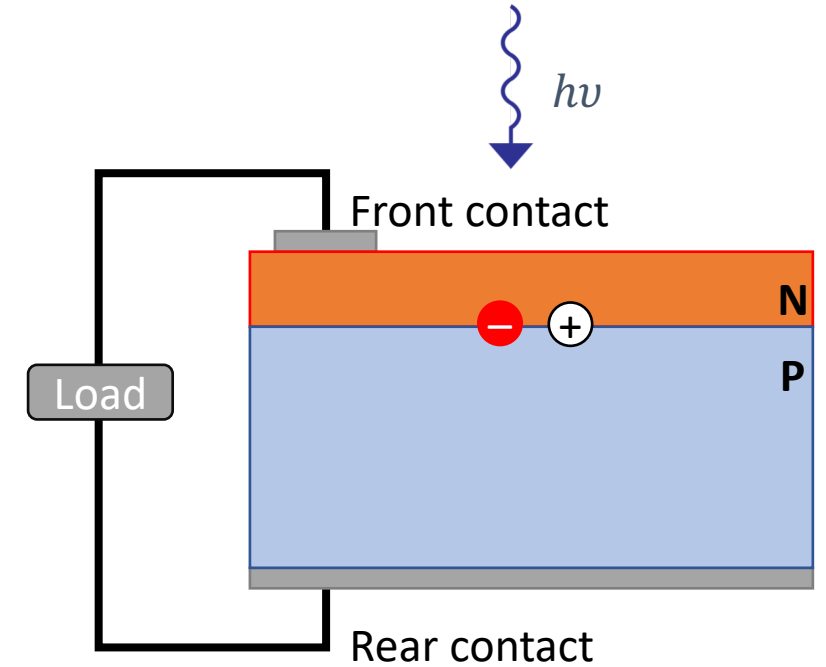
- In general, the n region is heavily doped and thin so that the light can penetrate through it easily.
- The p region is lightly doped so that most of the depletion region lies in the p side.
- Main two processes: carrier generation and carrier collection.
- Electron-hole pairs are generated by the incident photon $> E_g$. The electron-hole pairs exist, on average, for a length of time equal to the minority carrier lifetime before they recombine.
- The carriers are separated by the E-field existing at the p-n junction.



See the animation in <https://www.pveducation.org/pvcdrom/solar-cell-operation/light-generated-current>

EPFL pn Junction Solar Cell

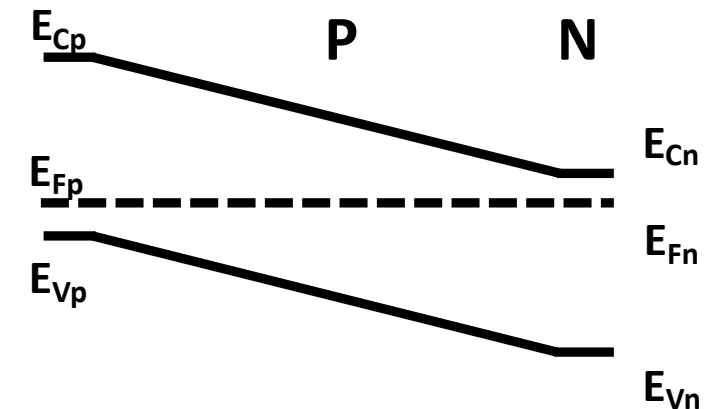
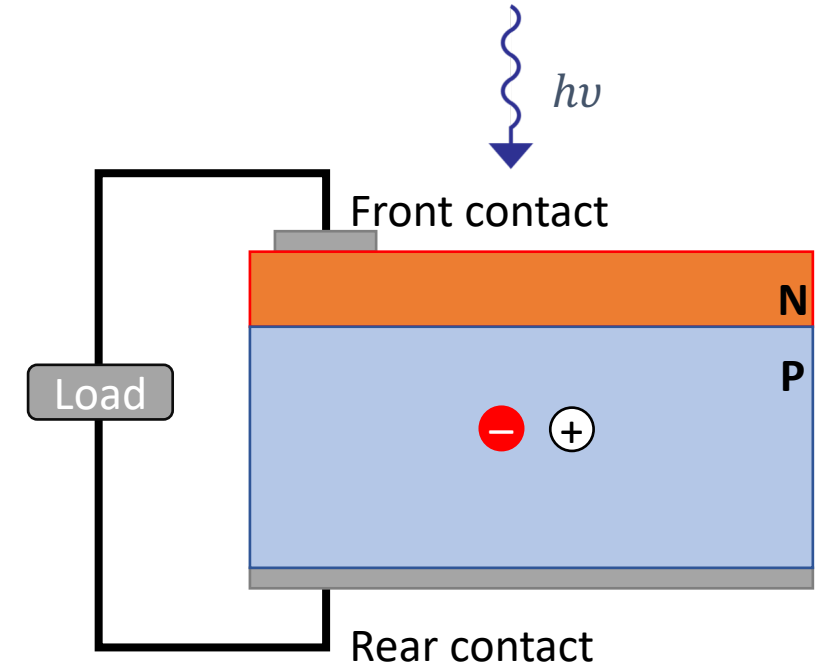
- In general, the n region is heavily doped and thin so that the light can penetrate through it easily.
- The p region is lightly doped so that most of the depletion region lies in the p side.
- Main two processes: carrier generation and carrier collection.
- Electron-hole pairs are generated by the incident photon $> E_g$. The electron-hole pairs exist, on average, for a length of time equal to the minority carrier lifetime before they recombine.
- The carriers are separated by the E-field existing at the p-n junction.



See the animation in <https://www.pveducation.org/pvcdrom/solar-cell-operation/light-generated-current>

EPFL pn Junction Solar Cell

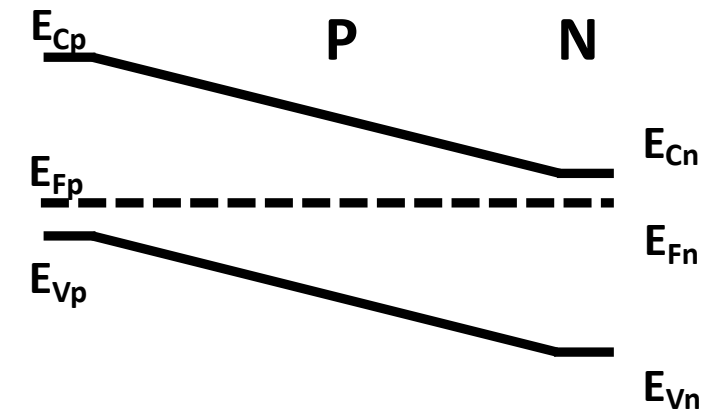
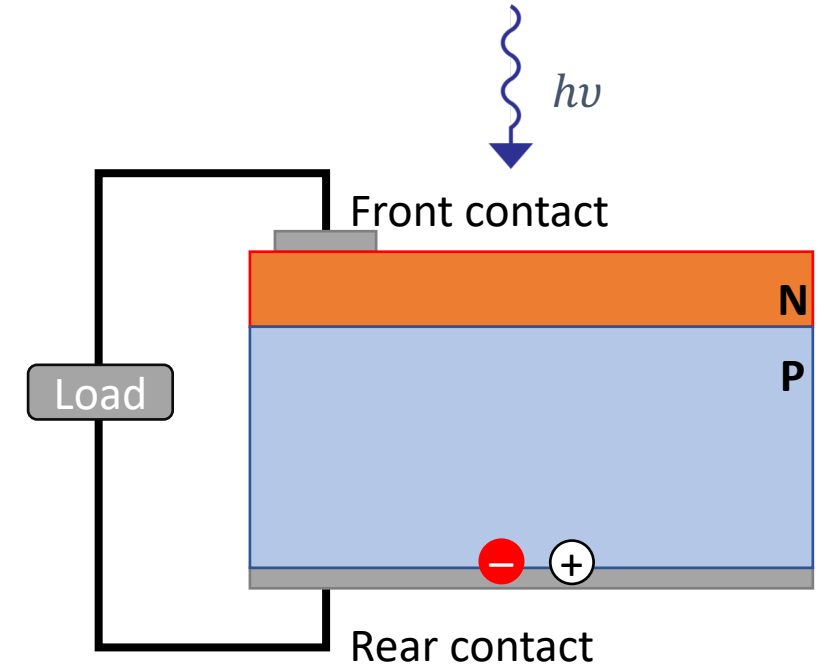
- In general, the n region is heavily doped and thin so that the light can penetrate through it easily.
- The p region is lightly doped so that most of the depletion region lies in the p side.
- Main two processes: carrier generation and carrier collection.
- Electron-hole pairs are generated by the incident photon $> E_g$. The electron-hole pairs exist, on average, for a length of time equal to the minority carrier lifetime before they recombine.
- The carriers are separated by the E-field existing at the p-n junction.



See the animation in <https://www.pveducation.org/pvcdrom/solar-cell-operation/light-generated-current>

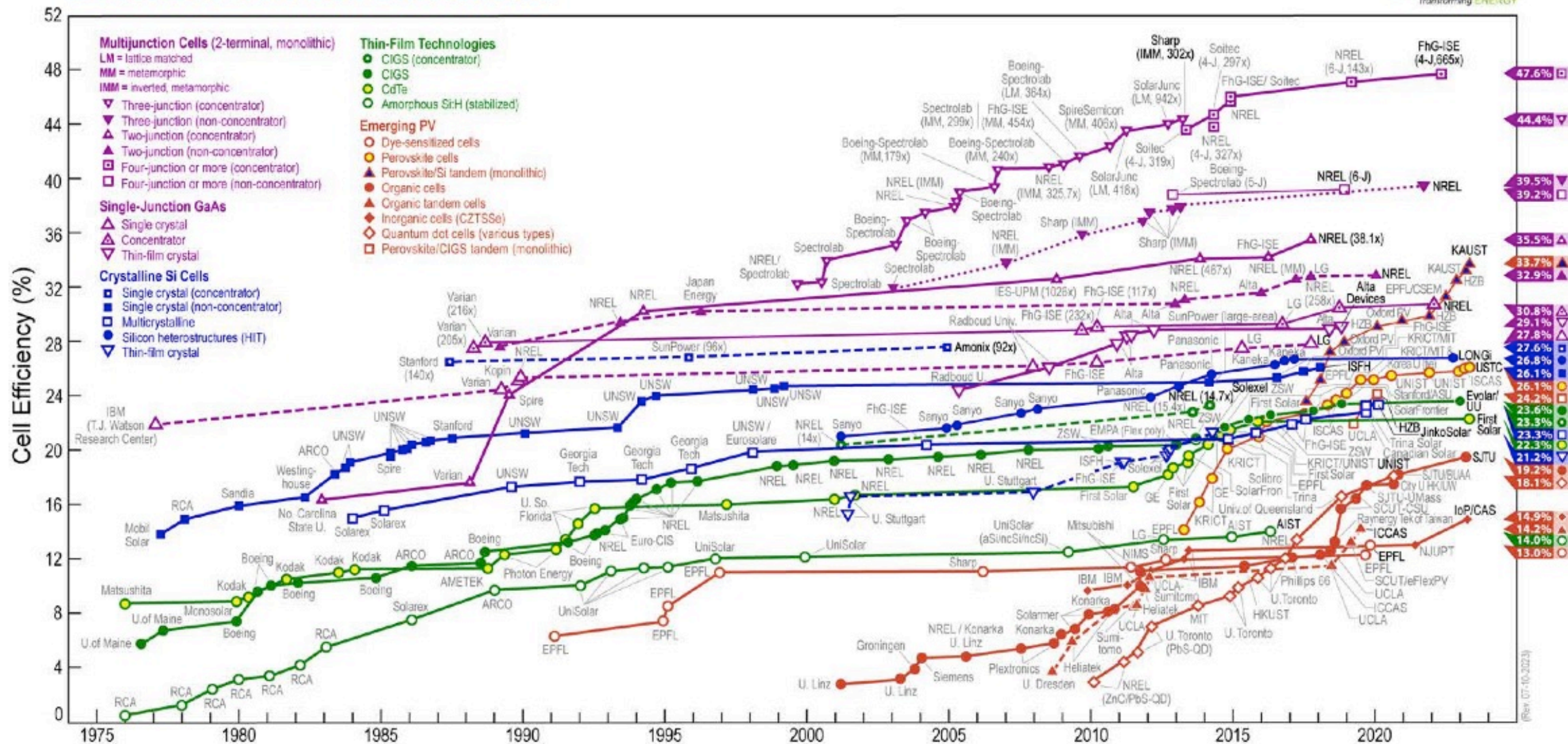
EPFL pn Junction Solar Cell

- In general, the n region is heavily doped and thin so that the light can penetrate through it easily.
- The p region is lightly doped so that most of the depletion region lies in the p side.
- Main two processes: carrier generation and carrier collection.
- Electron-hole pairs are generated by the incident photon $> E_g$. The electron-hole pairs exist, on average, for a length of time equal to the minority carrier lifetime before they recombine.
- The carriers are separated by the E-field existing at the p-n junction.

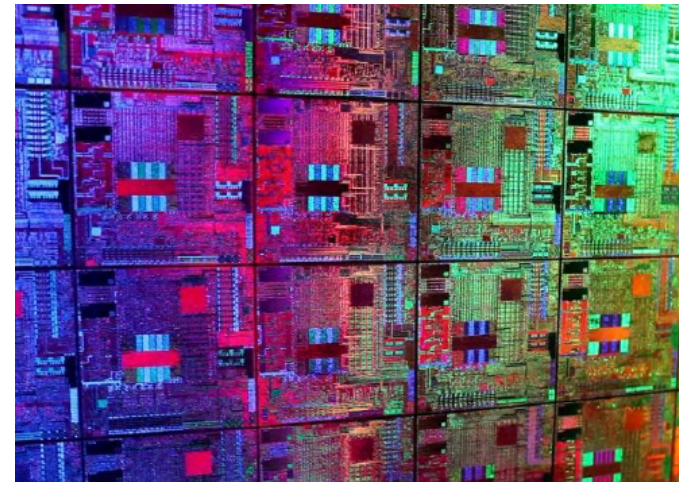
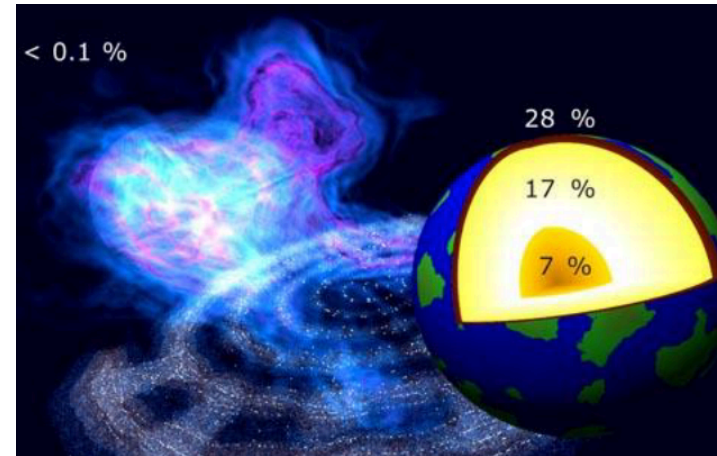


See the animation in <https://www.pveducation.org/pvcdrom/solar-cell-operation/light-generated-current>

Best Research-Cell Efficiencies

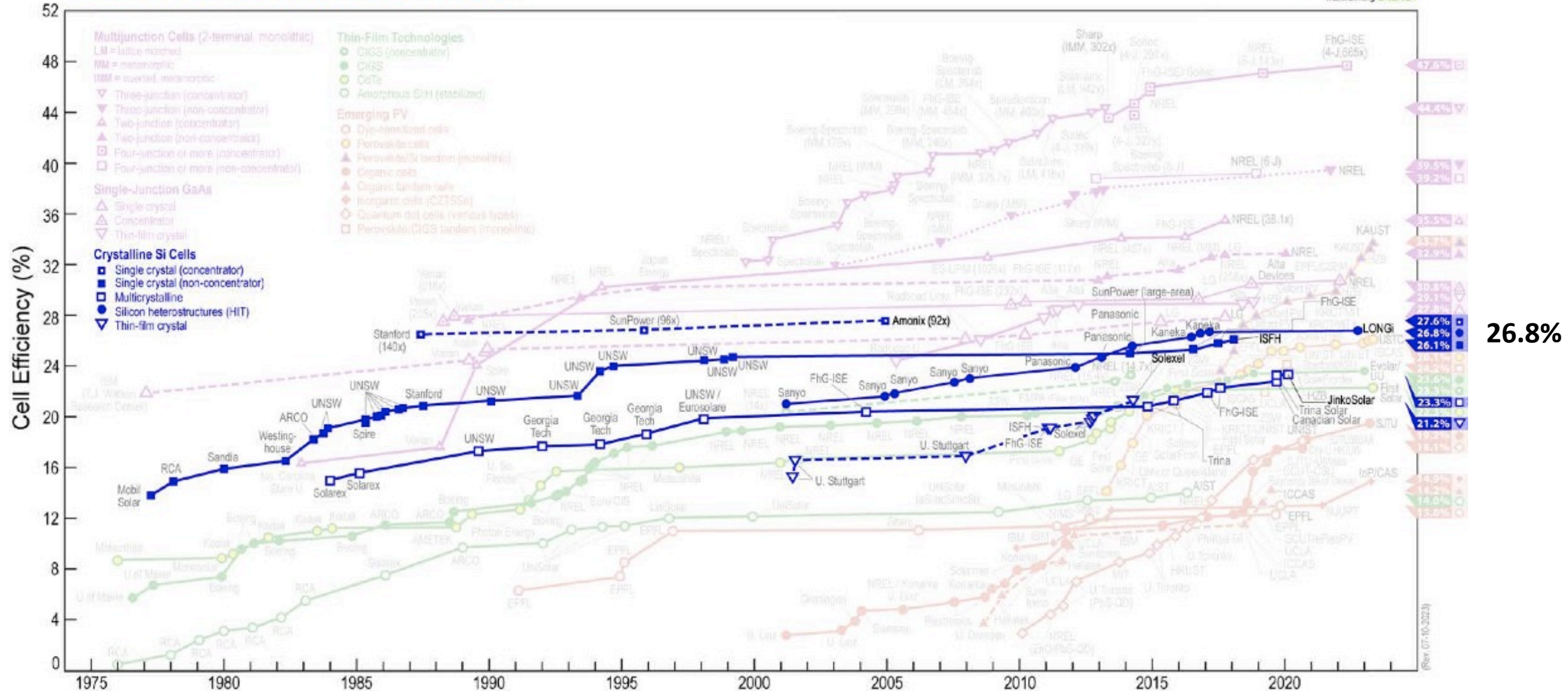


Si has suitable E_g , 1.12 eV
Doing is possible
Abundant and non-toxic
Mostly used in microelectronics



EPFL Type of Silicon for Solar Cells

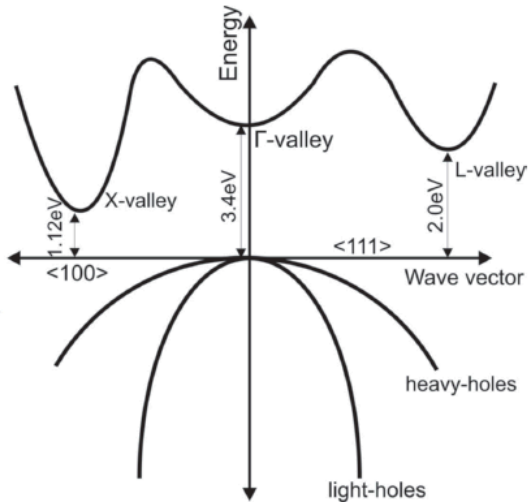
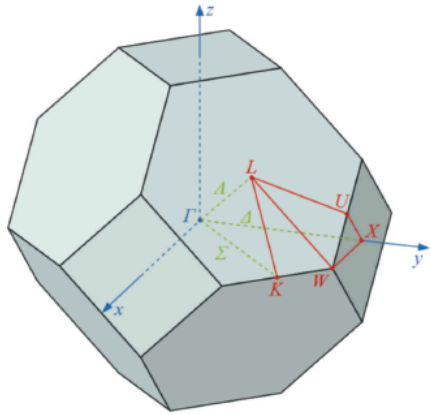
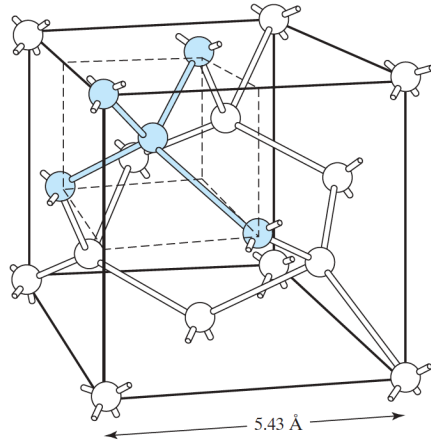
Best Research-Cell Efficiencies



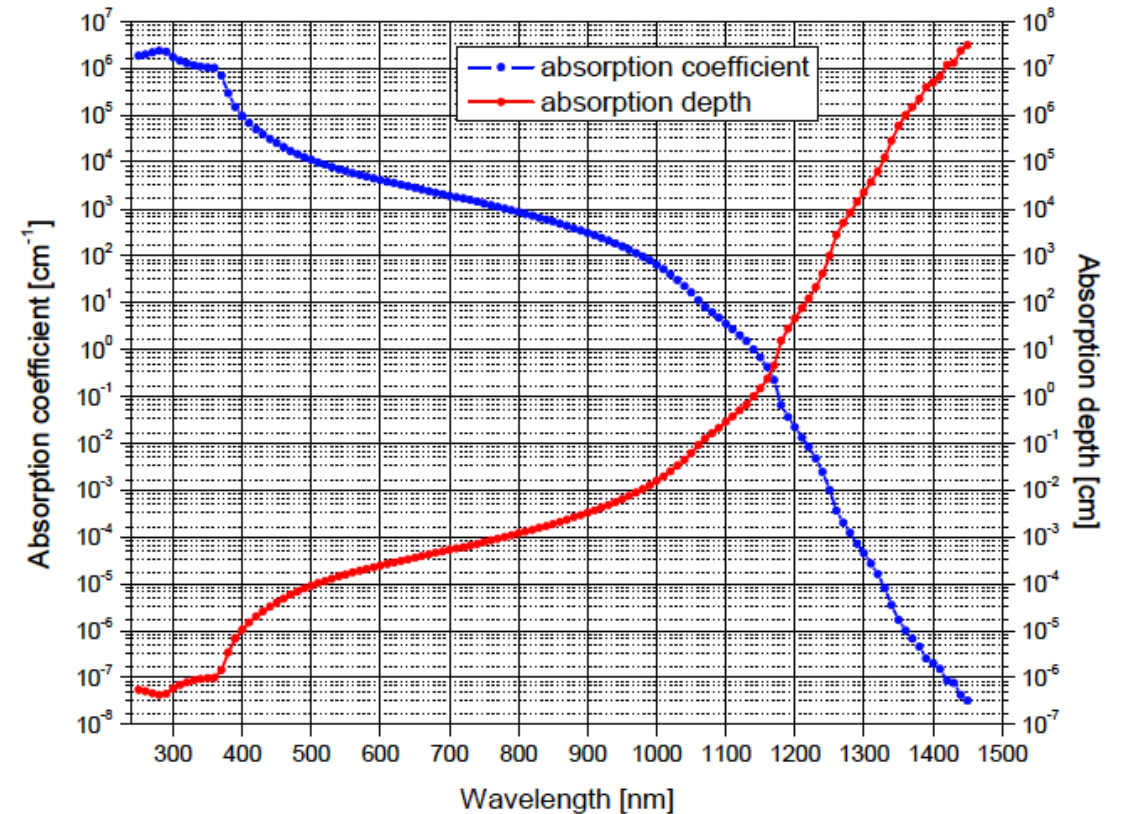
26.8%

EPFL Crystalline Silicon

Bond angle is $109^{\circ}28'$ and bond length is approximately $2.35 \text{ \AA}$.

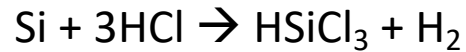
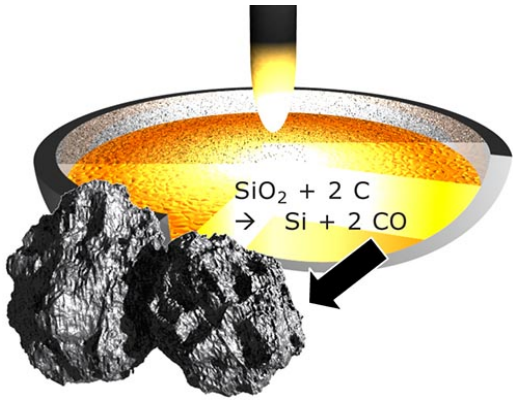


Indirect band gap is 1.12 eV

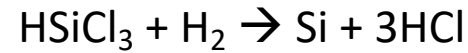


EPFL From Sand to Silicon Single Crystal

Reduction of SiO_2 with carbon to metallurgical grade silicon (>98%) in an electric arc furnace

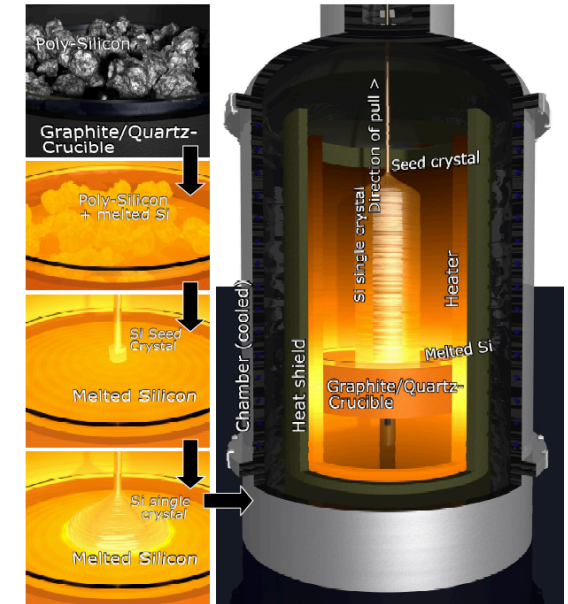


Purification of Silicon by distillation (Siemens Process)

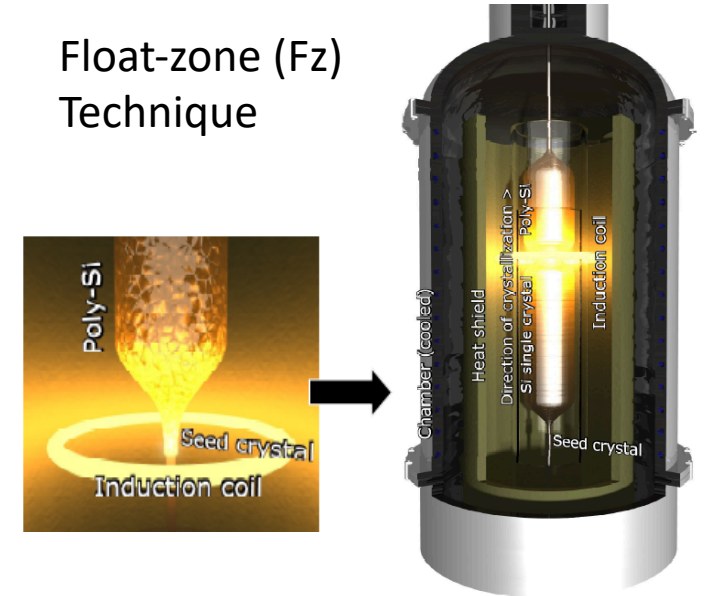


Electronic grade poly silicon (9N, impurities $< 10^{14} \text{ cm}^{-3}$)

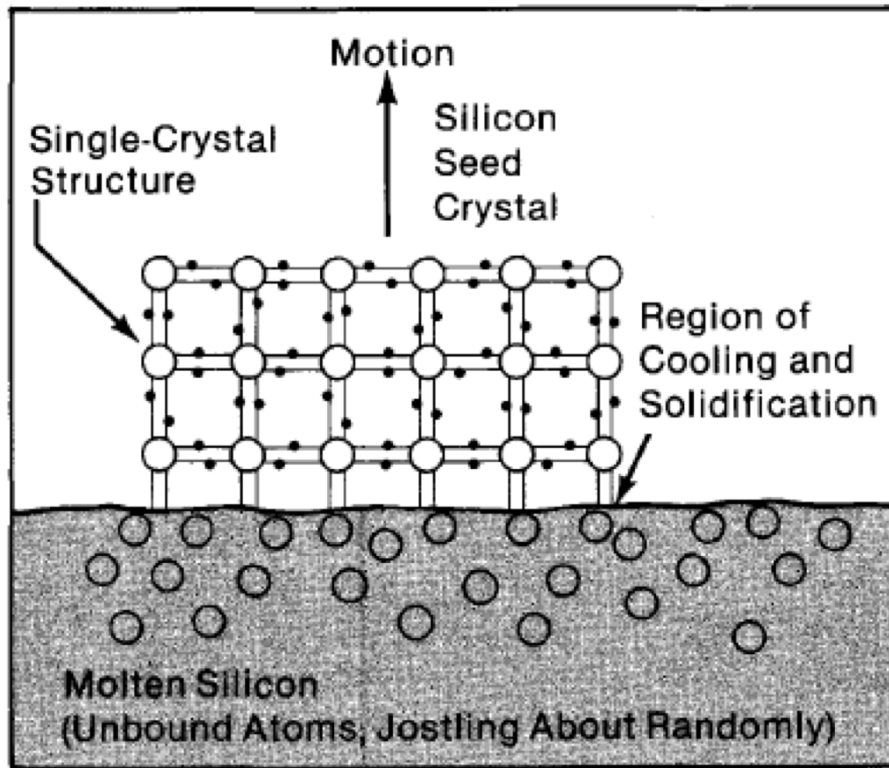
Czochralski (Cz) Technique



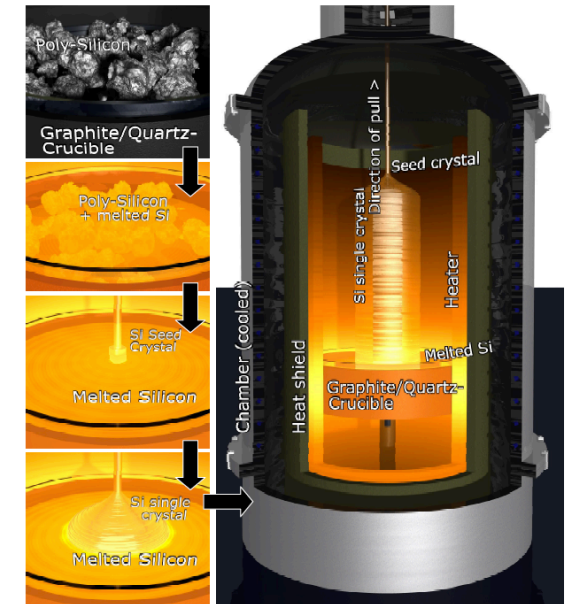
Float-zone (Fz) Technique



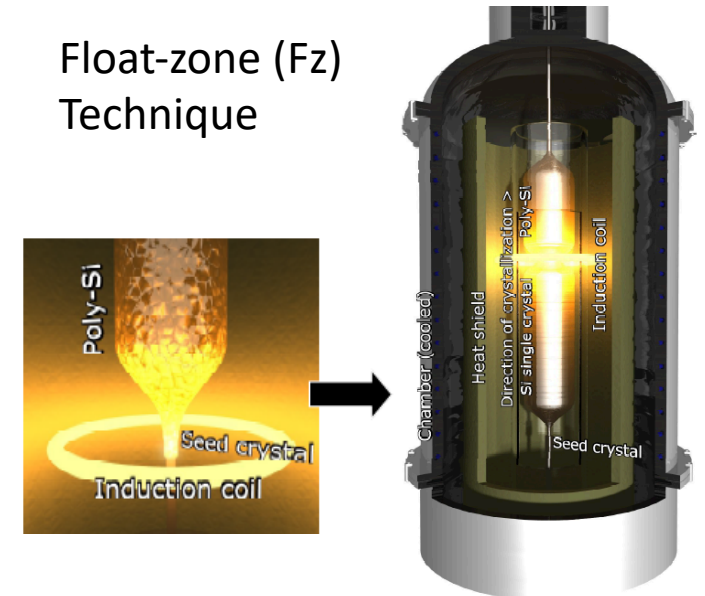
EPFL From Sand to Silicon Single Crystal



Czochralski (Cz) Technique

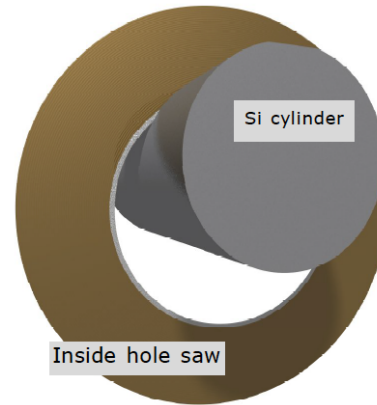


Float-zone (Fz) Technique



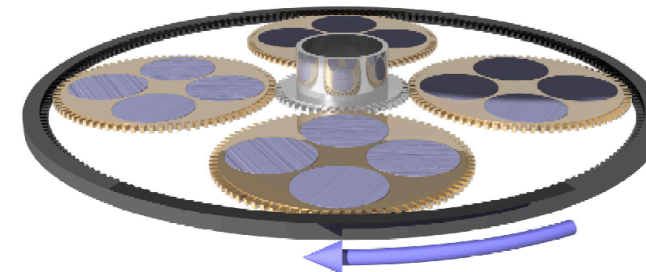
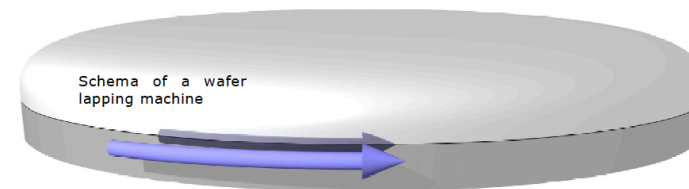
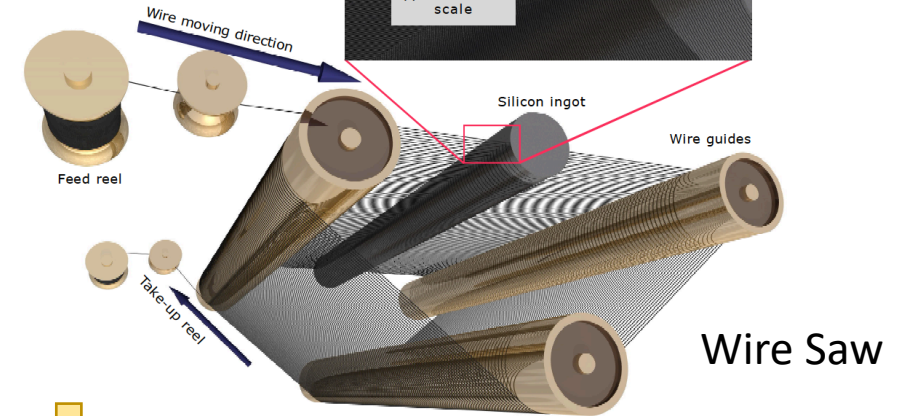
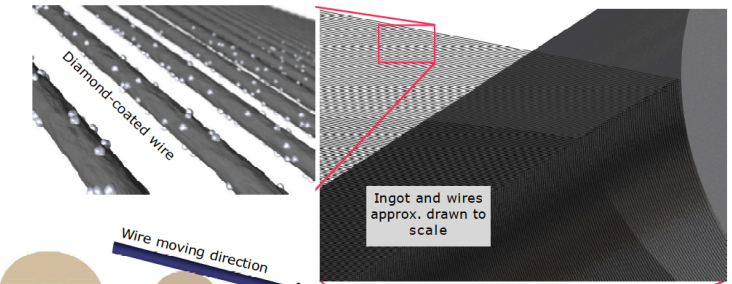
EPFL From Single Crystal to Polished Wafer

Grinding



Inside Hole Saw

Dicing



Lapping



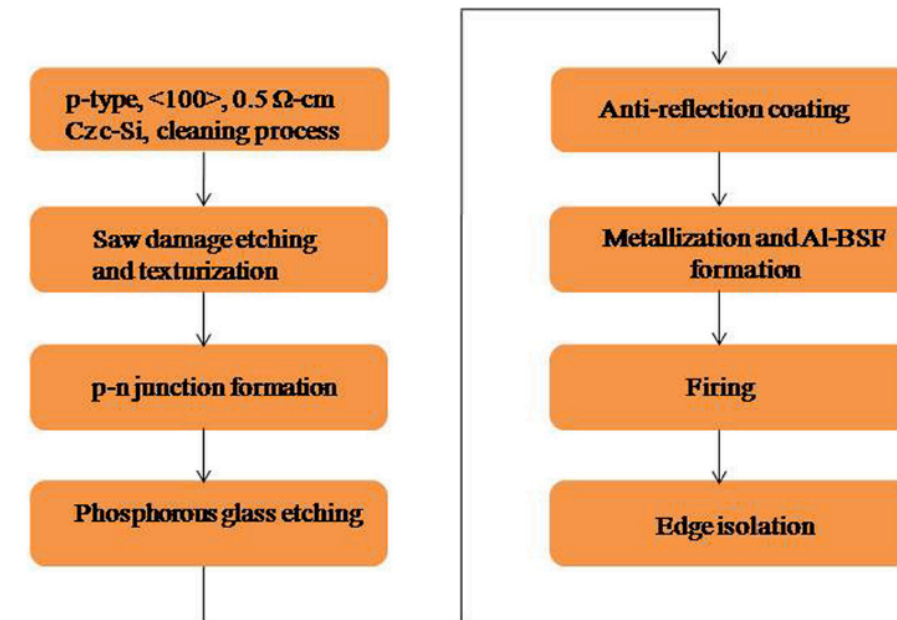
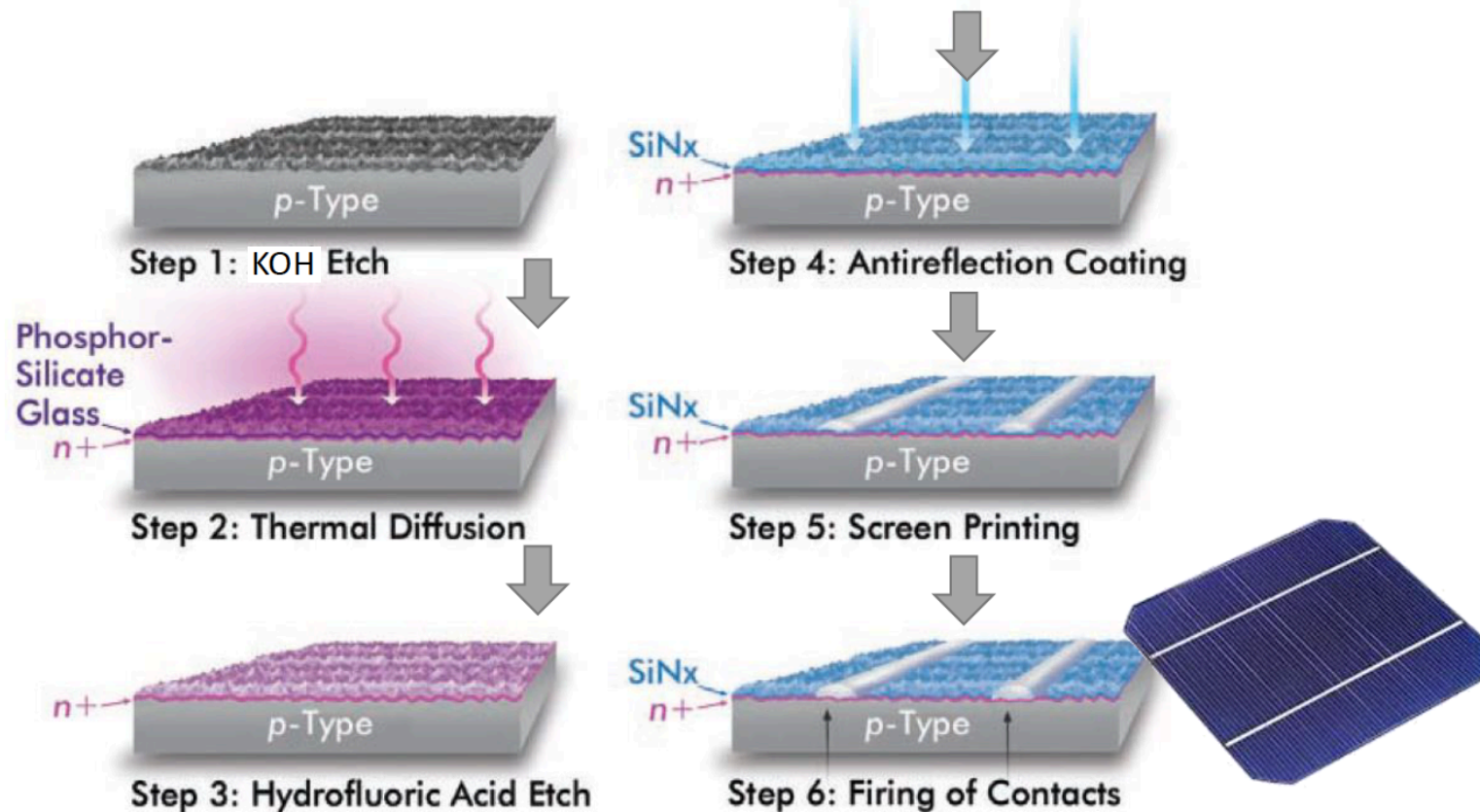
Etching, Polishing, Cleaning

EPFL Single Crystalline Si Solar Cell Fabrication Technologies

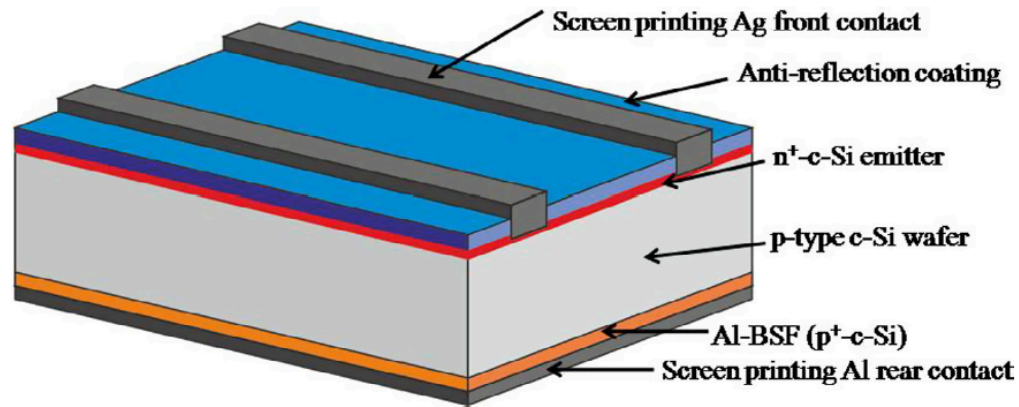
Screen Printed Solar Cells: <https://www.pveducation.org/pvcdrom/manufacturing-si-cells/screen-printed-solar-cells>

Buried Contact Solar Cells: <https://www.pveducation.org/pvcdrom/manufacturing-si-cells/buried-contact-solar-cells>

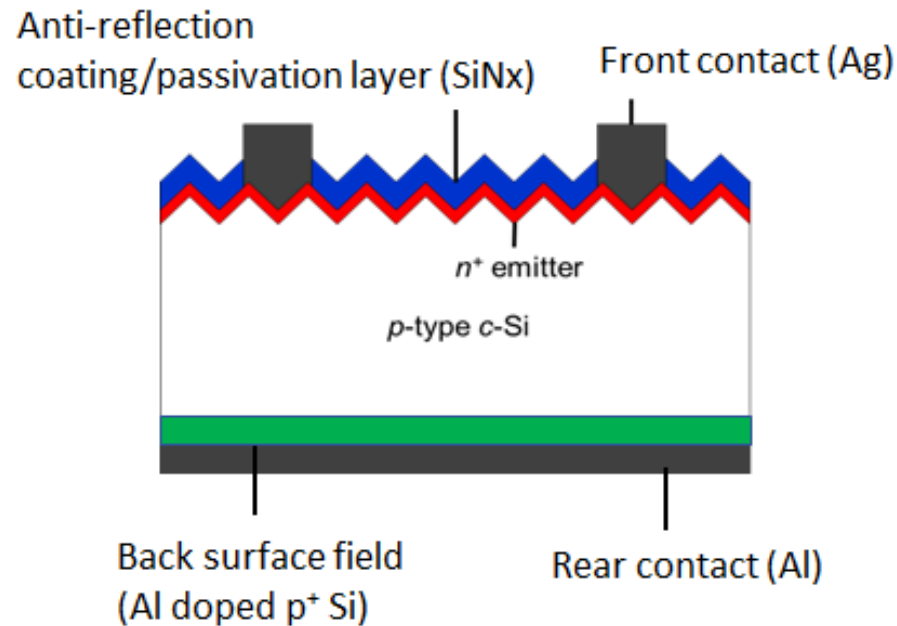
High Efficiency Solar Cells: <https://www.pveducation.org/pvcdrom/manufacturing-si-cells/high-efficiency-solar-cells>



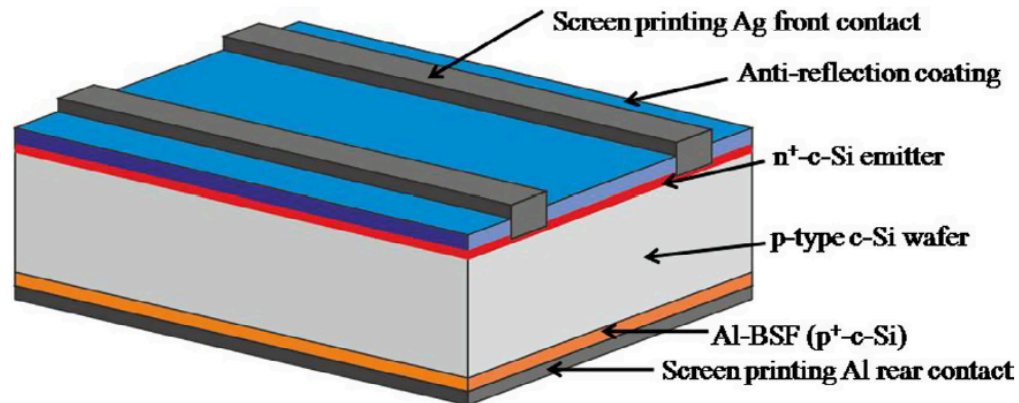
Conventional Si Solar Cell: Al-back surface field (BSF) solar cell



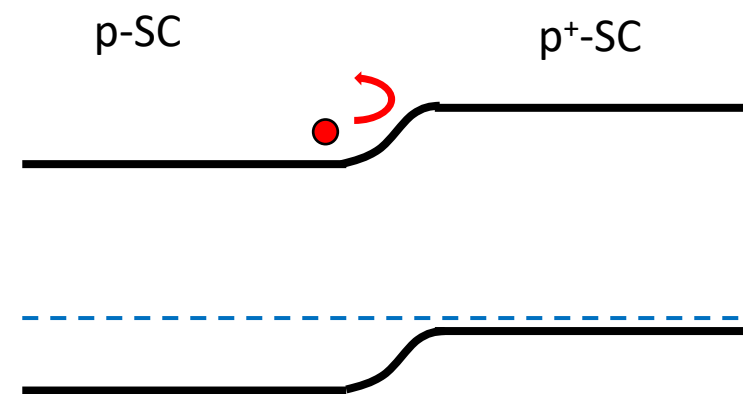
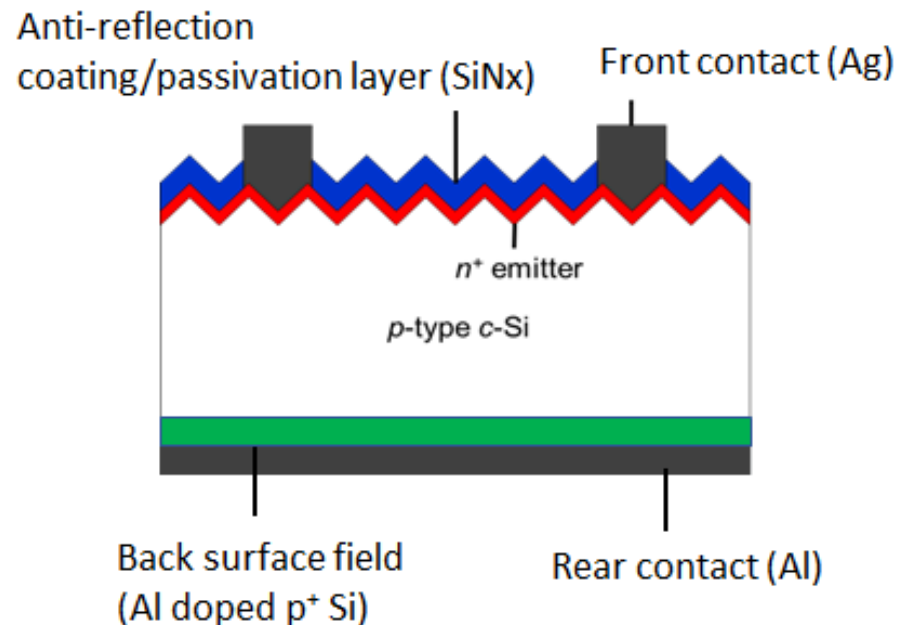
- At the rear side, a heavily Al-doped p⁺-region in p-type c-Si forms a high-low (p⁺/p) junction known as Al-BSF.
- The potential barrier at the high-low (p⁺/p) junction drives electrons away from reaching the back electrode and towards the pn junction (Reduced surface recombination velocity (SRV)) → Increase in V_{oc} and J_{sc} .



Conventional Si Solar Cell: Al-back surface field (BSF) solar cell

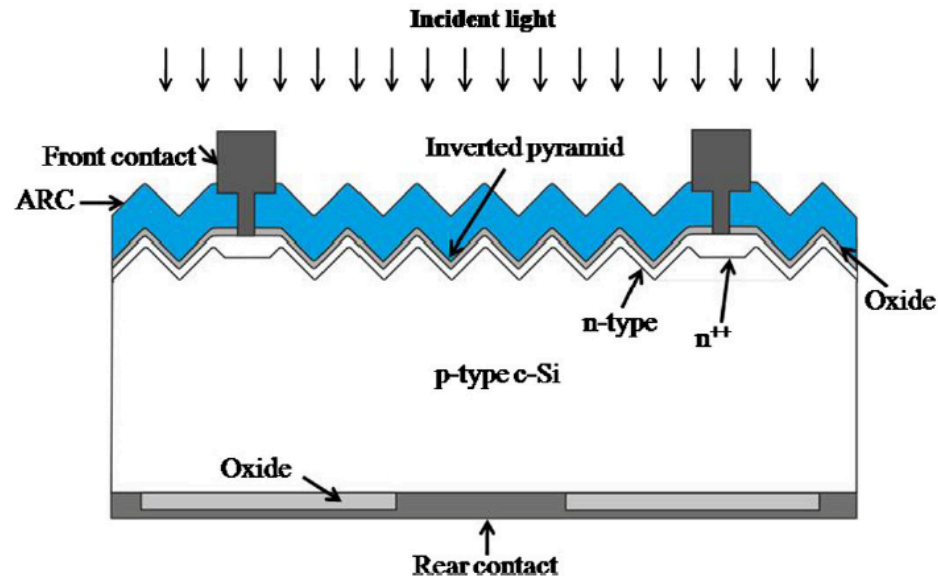


- At the rear side, a heavily Al-doped p⁺-region in p-type c-Si forms a high-low (p⁺/p) junction known as Al-BSF.
- The potential barrier at the high-low (p⁺/p) junction drives electrons away from reaching the back electrode and towards the pn junction (Reduced surface recombination velocity (SRV)) → Increase in V_{oc} and J_{sc} .

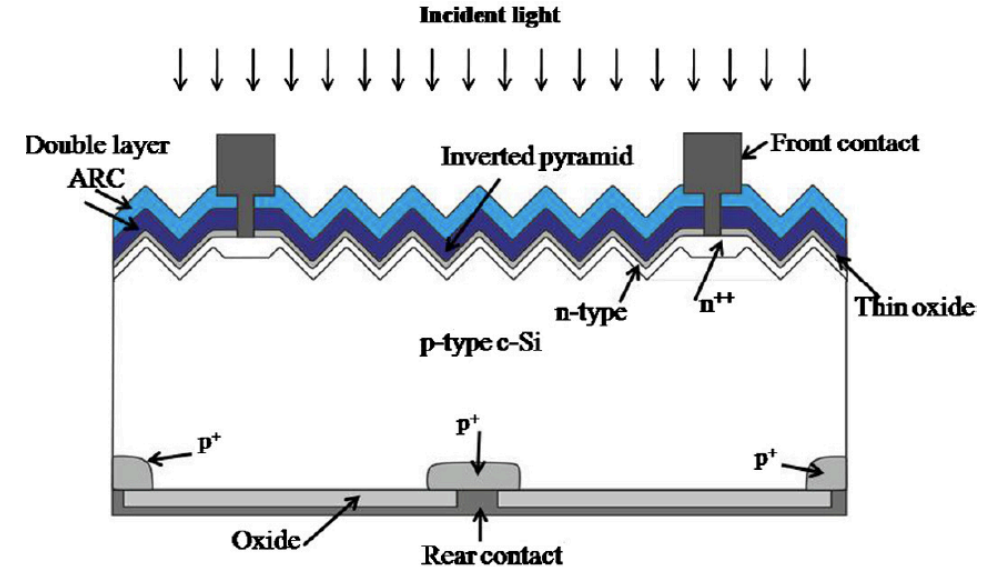


EPFL PERC and PERL Solar Cells

High Efficiency Solar Cell: passivated emitter rear contact (PERC) and passivated emitter rear locally-diffused (PERL) solar cell

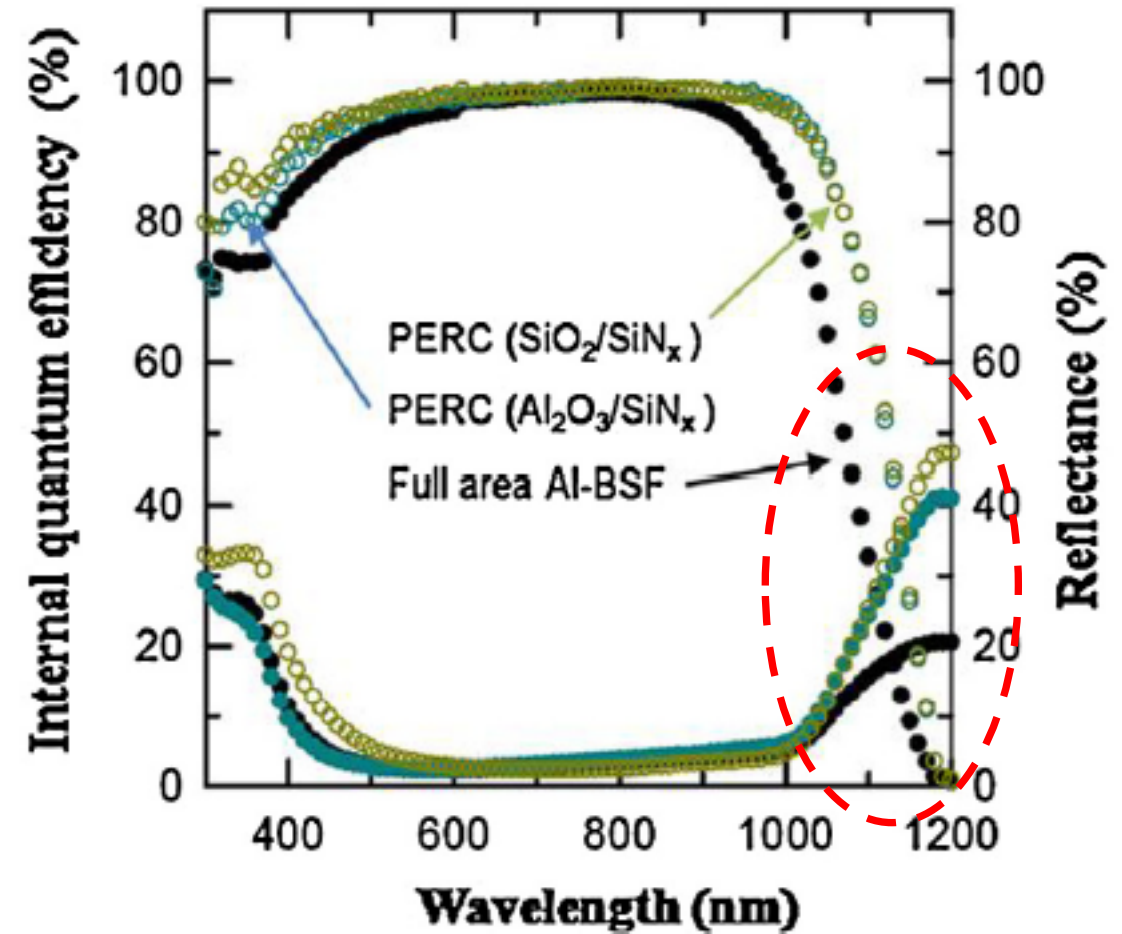
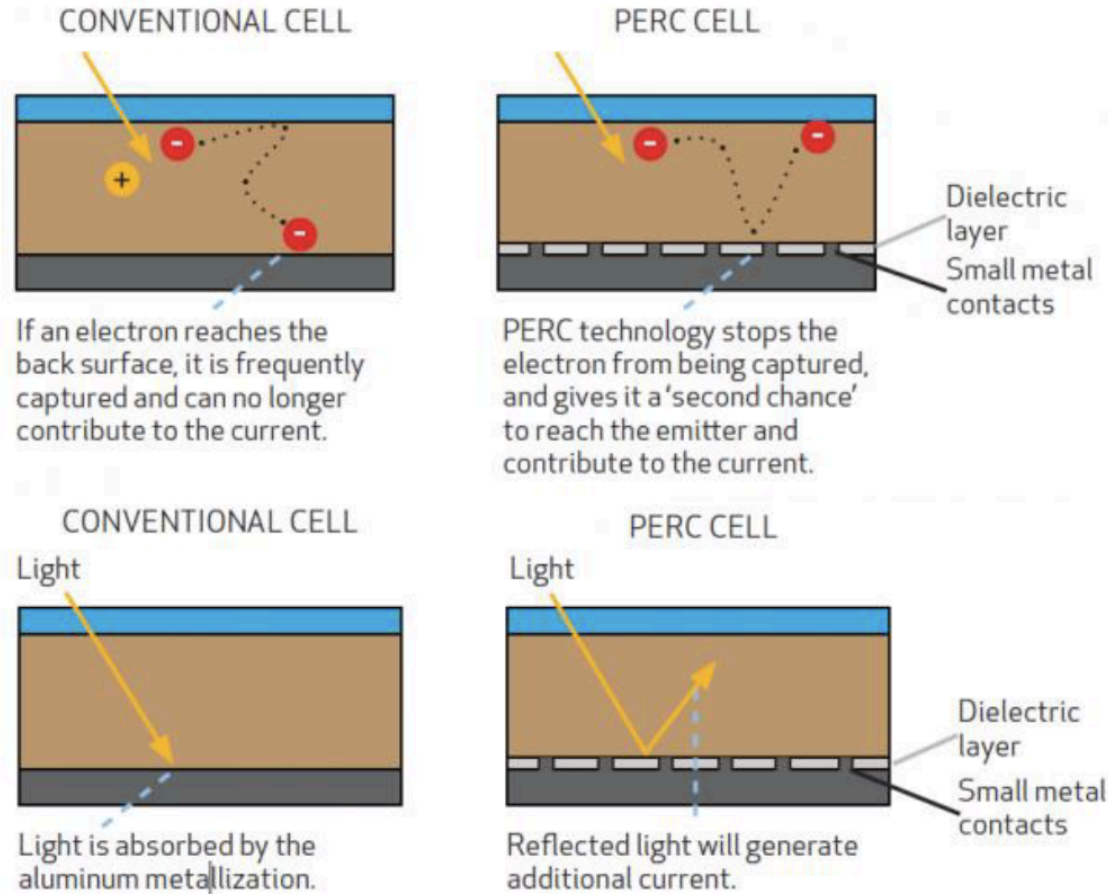


Rear side dielectric passivation layer (Al_2O_3): reduced surface recombination and improved reflection.



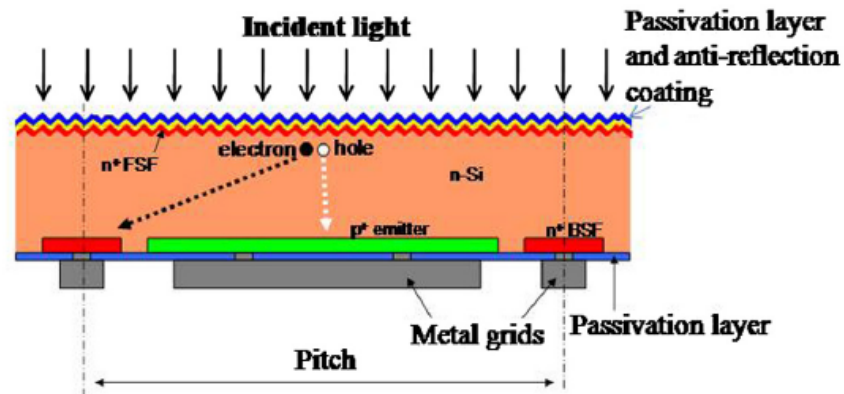
Electric field in the BSF region between p⁺/p junction drives electrons away towards the pn junction and reduces surface recombination at the defective metal/c-Si interface.

21.2% with PERC and 25% with PERL

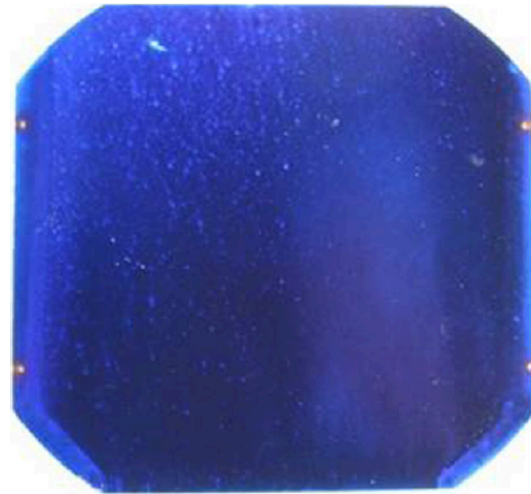


Dullweber T. et al., *Prog Photovolt: Res Appl*; 20:630–8 (2012)

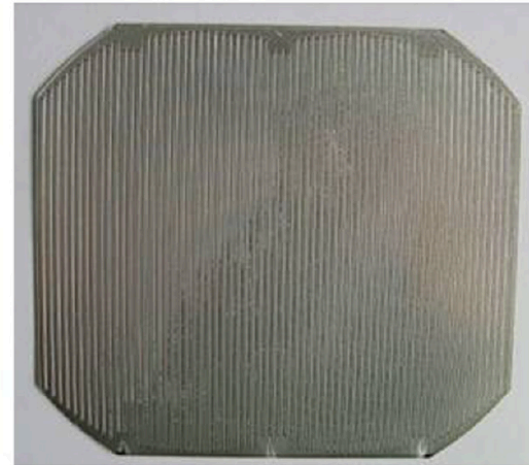
Interdigitated back contact (IBC) c-Si solar cells



- Major advantage: No front side metallization grid → Zero shading losses → High J_{sc}
- Passivation and light trapping properties can be optimized for the front side
- No limit for the width and thickness of metallization on the back side: Reduced series R
- Advantageous for the module manufacturing because of co-planar interconnection of the back-contact

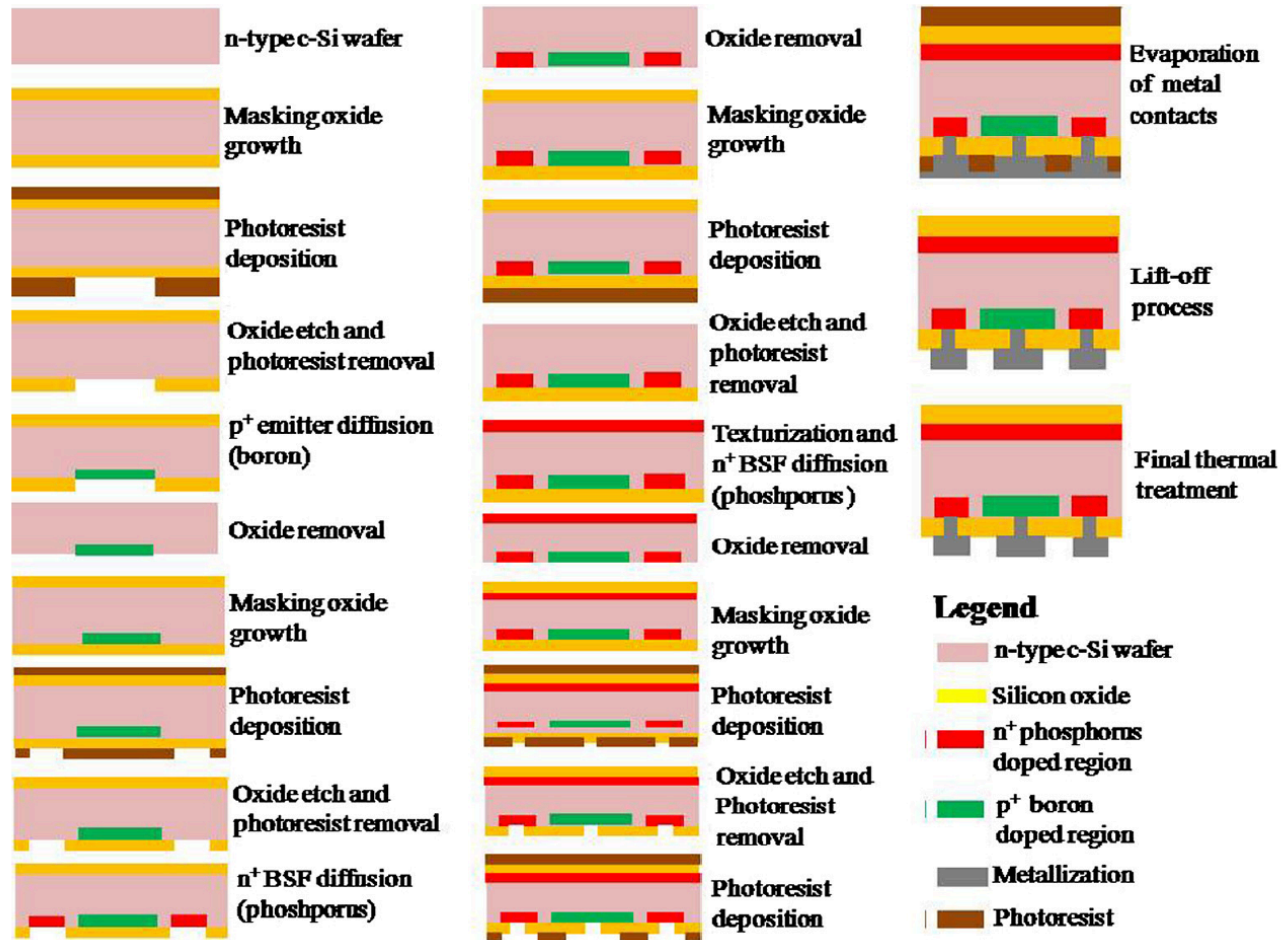


Grid less front side (147.4 cm²)



Rear side

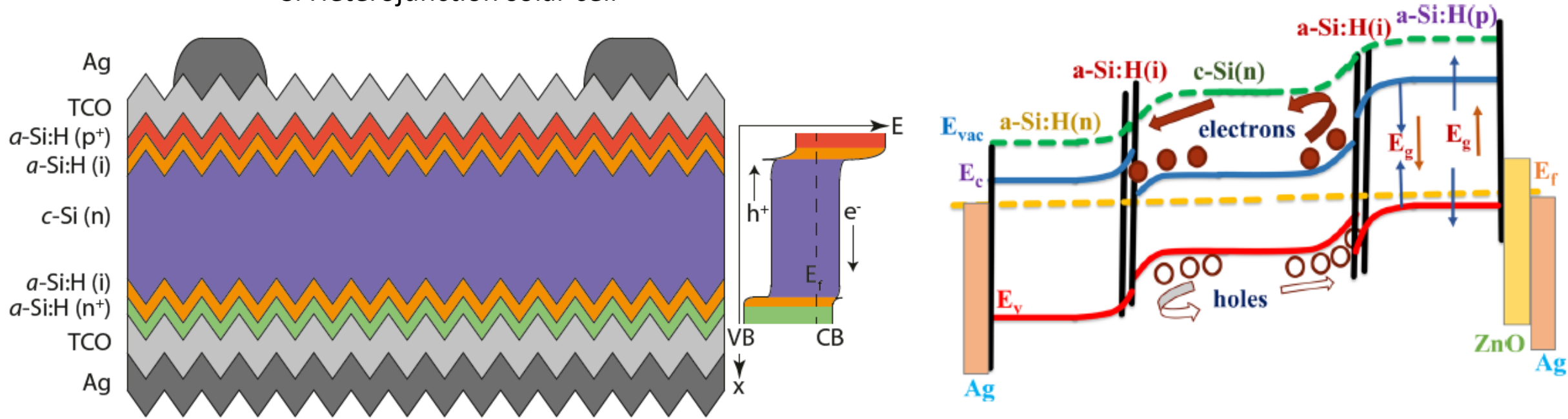
EPFL IBC c-Si Solar Cells



- The complexity of the processing technology: Example of a complex laboratory scale process flow for the IBC solar cell processing using photolithography and high-temperature diffusion processes.
- Photolithography is however not a cost-effective process for mass production in the photovoltaic industry.
- High accuracy masking steps are required to avoid shunting between p-type and n-type electrodes.
- Highly pure, lightly doped Fz c-Si wafers with diffusion length at the least four times higher than the thickness of the c-Si wafer and the lifetime of 1 – 3 ms are required.

EPFL Silicon Heterojunction Solar Cell

Si Heterojunction solar cell



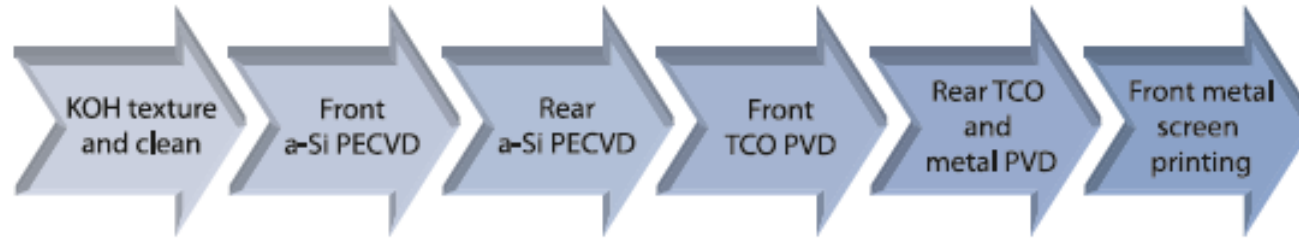
Wolf et al., *Green*, 2, 7 – 24 (2012)

V. Kanneboina, *J. Comp. Electronics*, 20:344 (2021)

- Doped (n or p) a-Si:H over-layers are used to form junctions as electron and hole collectors, allowing the fabrication of nearly recombination-free contacts.
- Long carrier lifetime by a-Si:H over-layers
- Charges trickle through the buffer layers sufficiently slowly to build up a high voltage e.g > 730 mV.

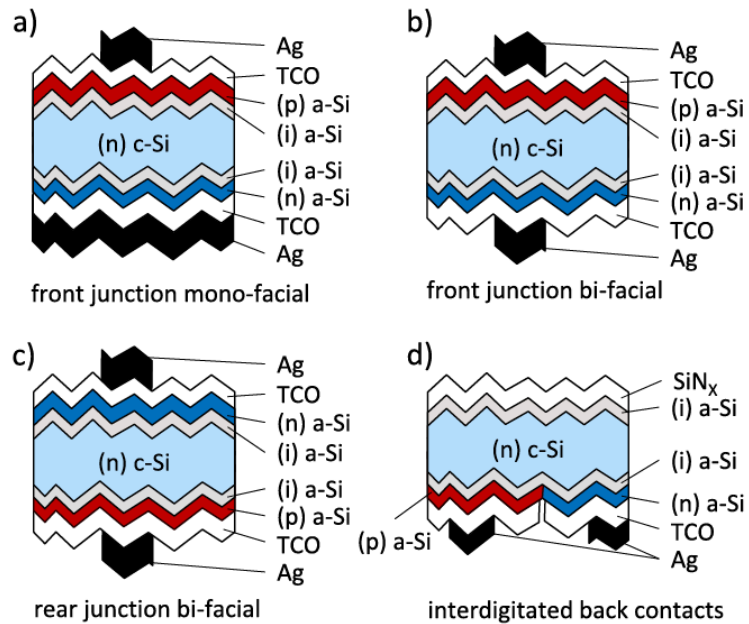
EPFL Silicon Heterojunction Solar Cells

Basic process steps for Si Heterojunction solar cell: low temperature process <200 °C



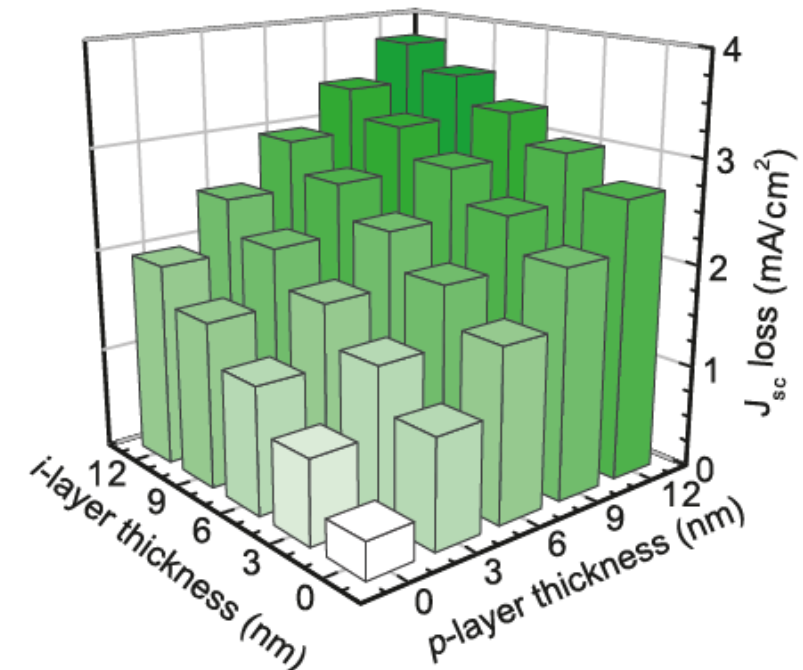
Wolf et al., *Green*, 2. 7 – 24 (2012)

Device architectures for SHJ solar cells.



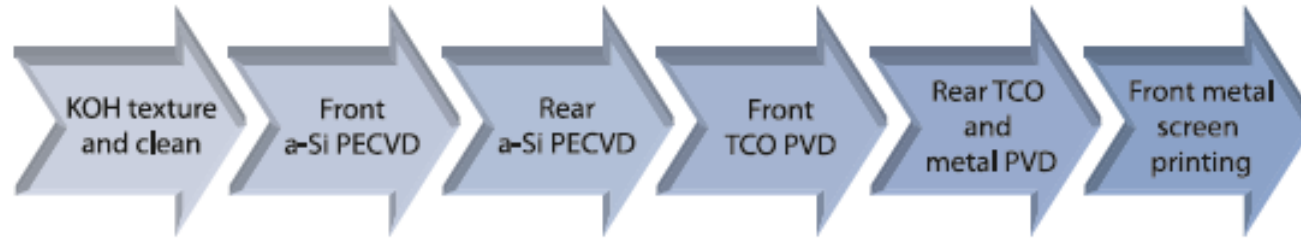
Haschke et al., *Solar Energy Mater. Solar Cells*, 187. 140 – 153 (2018)

Estimate of the losses in J_{sc} below 600 nm associated with increasing intrinsic and p-type layer thicknesses: bandgap of a-Si:H (1.7–1.9 eV)



EPFL Silicon Heterojunction Solar Cells

Basic process steps for Si Heterojunction solar cell: low temperature process <200 °C

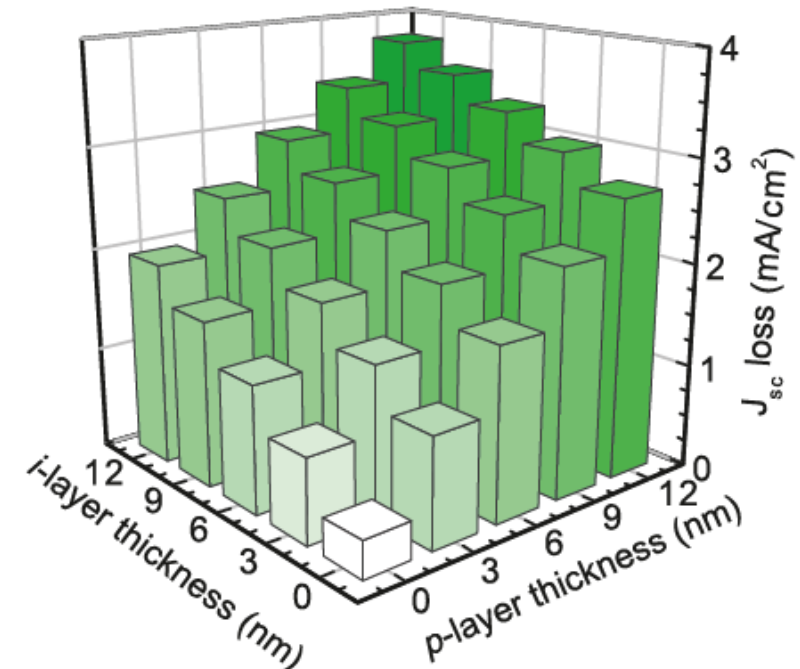


Wolf et al., *Green*, 2. 7 – 24 (2012)

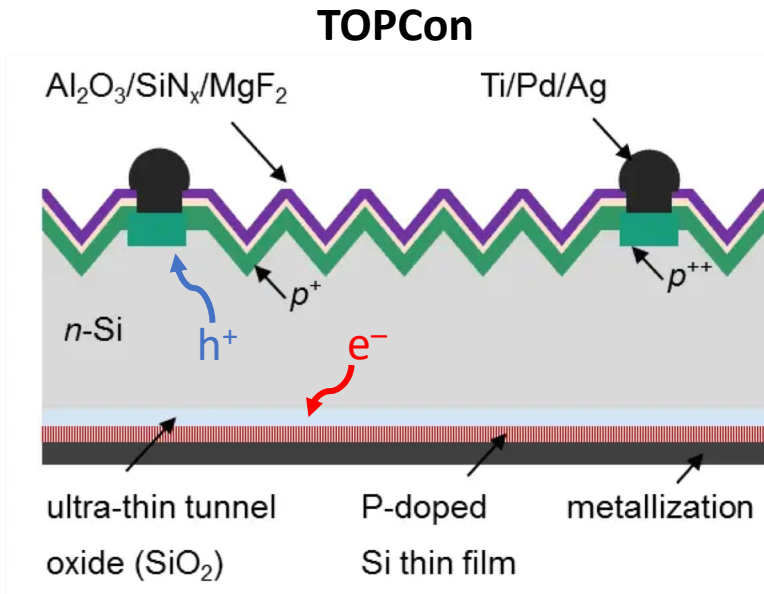
Estimate of the losses in J_{sc} below 600 nm associated with increasing intrinsic and p-type layer thicknesses: bandgap of a-Si:H (1.7–1.9 eV)

Solution!

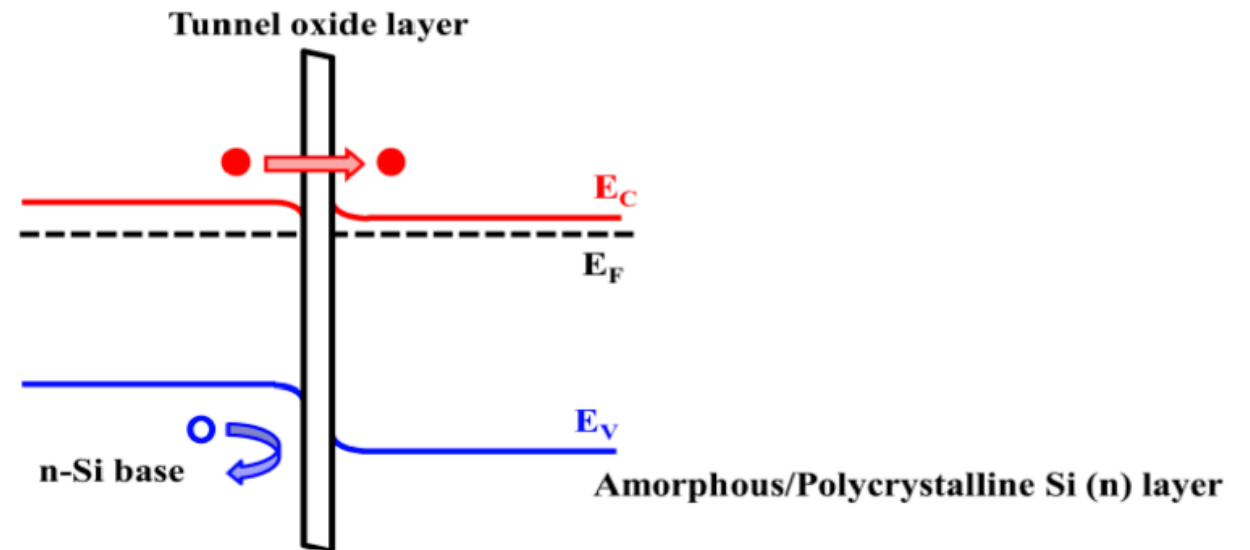
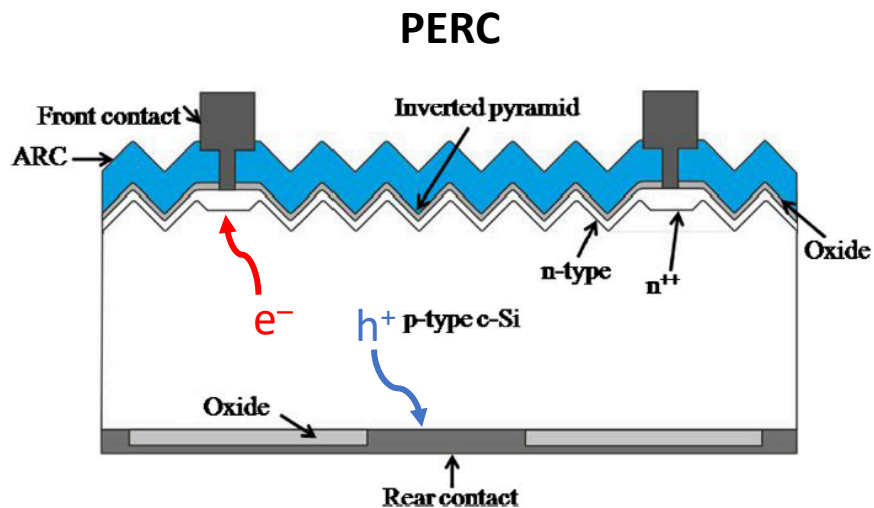
- Improving TCO transparency.
- Replacing a-Si:H with microcrystalline Si, which has features a higher doping.
- Combination with IBC structure.
- Thinner wafer (general trend for all c-Si PV technologies) possible to further increase V_{oc} .



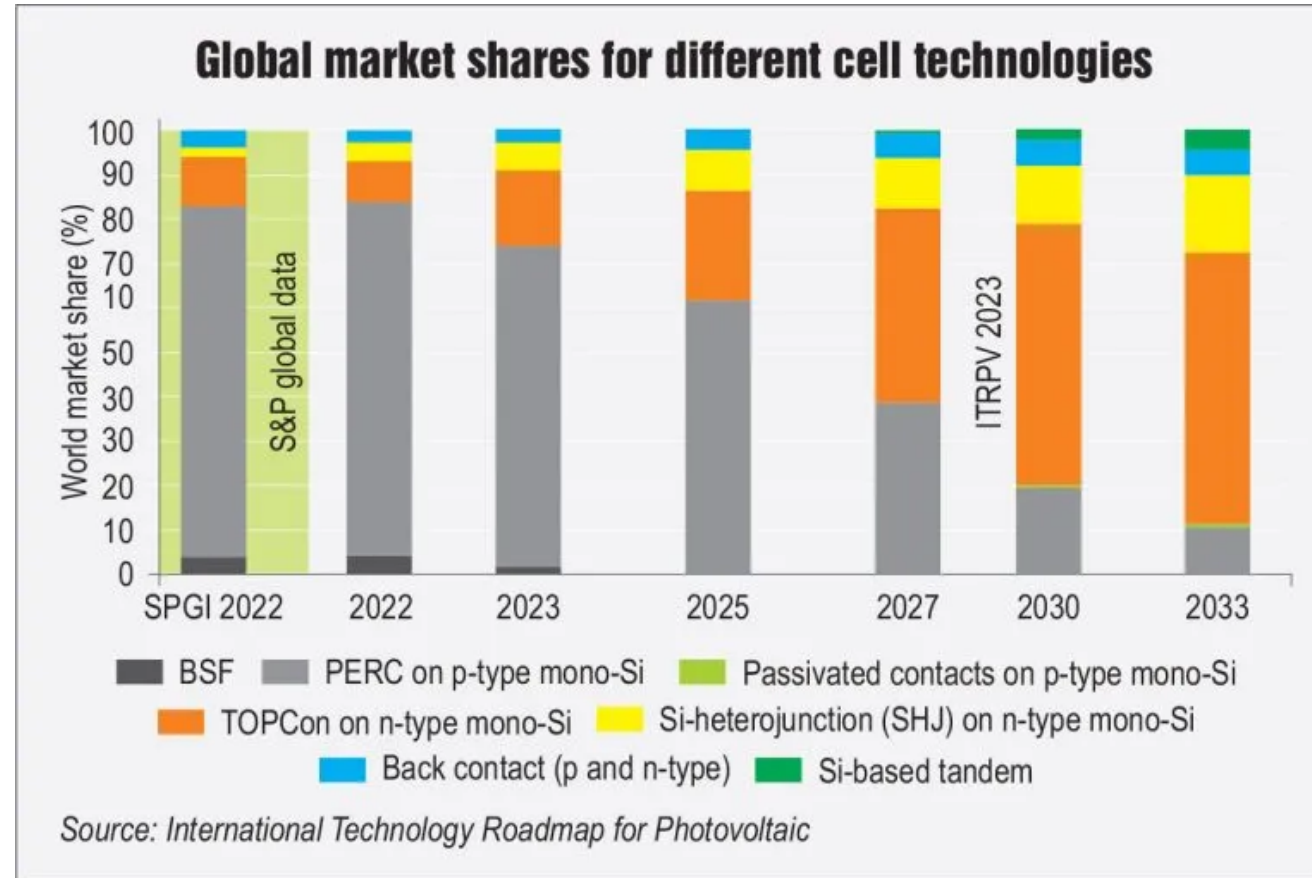
EPFL TOPCon Silicon Solar Cell



- The term TOPCon stands for **Tunnel Oxide Passivated Contact** and the architecture was presented by researchers at the Fraunhofer Institute for Solar Energy Systems in Freiburg in 2013.
- A very thin layer of silicon oxide (just a few nanometers) is applied to the surface of the solar cell and the SiO_2 layer passivates the surface, i.e. low surface recombination.
- However, the layer is so thin that the current can “tunnel through”.



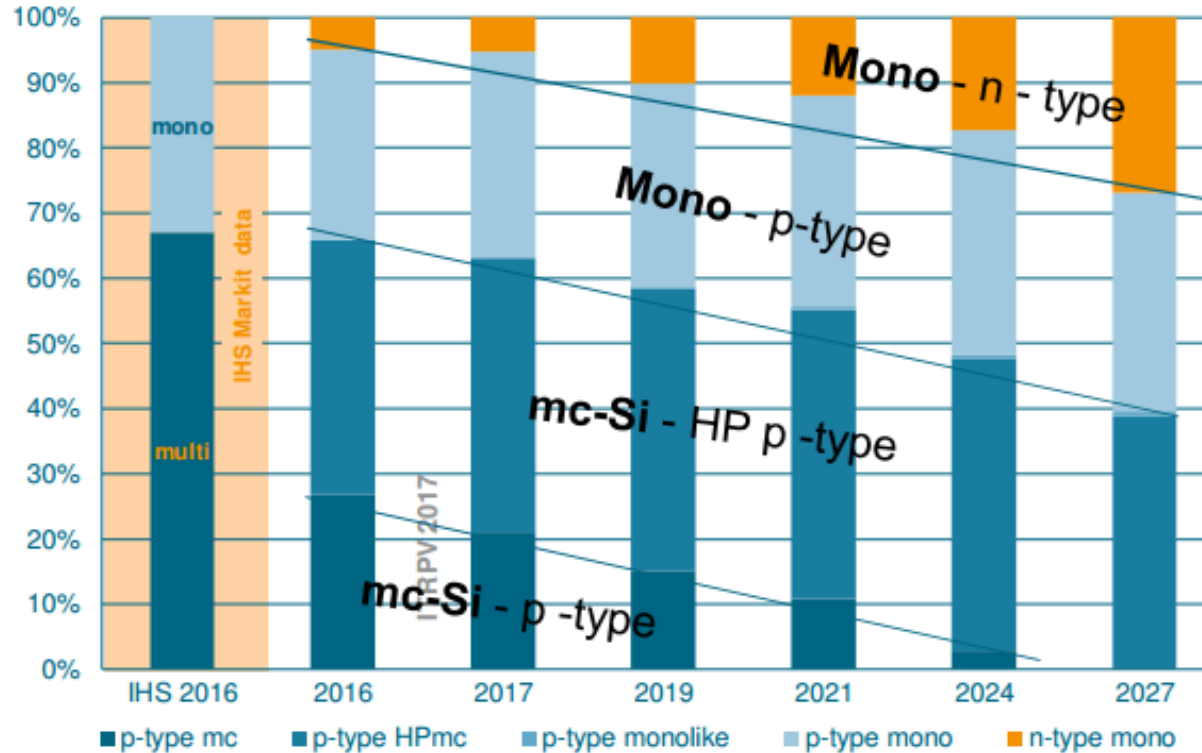
EPFL Trend for Single Crystalline Si Solar Cells



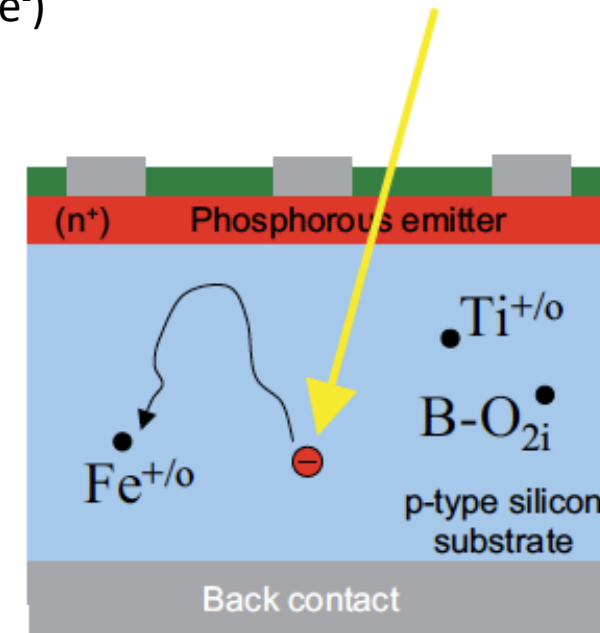
	PERC	TOPCon	HJT	IBC
Efficiency in mass production	23.50 %	24.80 %	25.80 %	25.00 %
Efficiency in lab	24.50 %	26.40 %	26.81 %	25.20 %

EPFL Trend for Single Crystalline Si Solar Cells

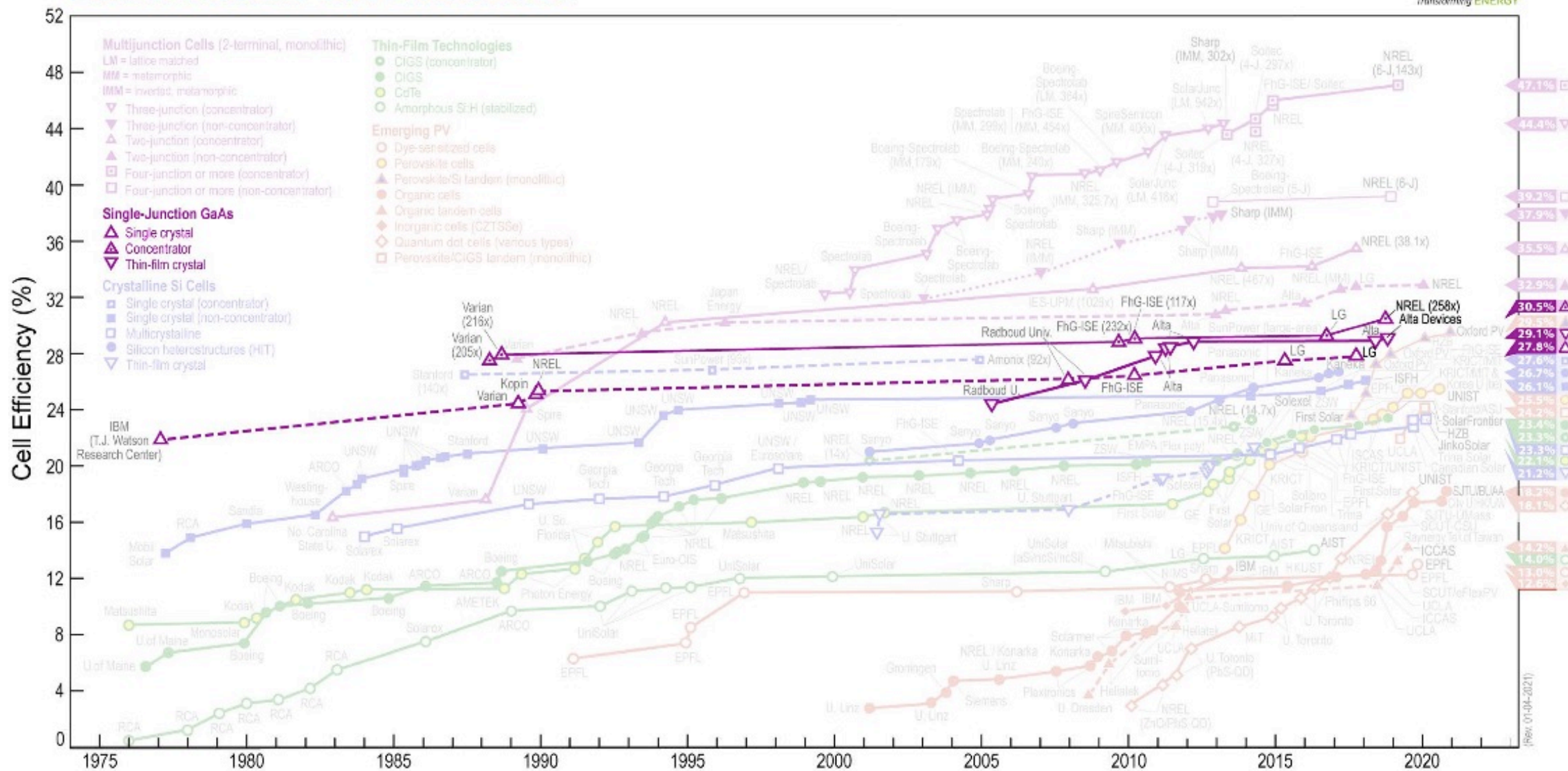
Trend: share of c-Si material types



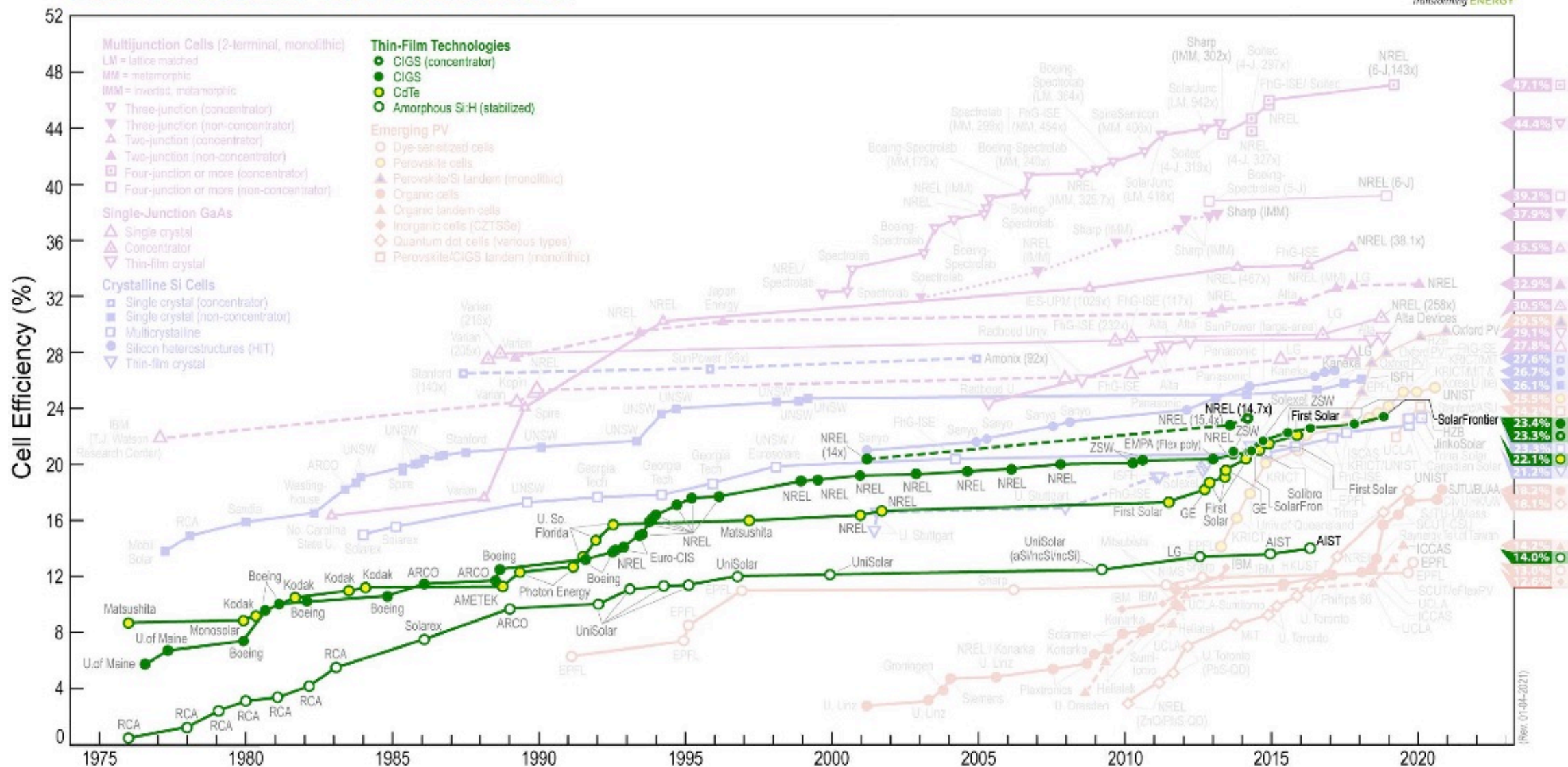
- Boron doped p-type Cz water: Boron (dopant) and oxygen (growth process impurity) forms a boron-oxygen related metastable defect upon illumination
→ Solution: Boron to Gallium dopant
FZ instead of Cz
Regeneration process to remove the defect
- Transition metal defects, Fe in p-type wafers have an increased capture rate for minority carriers in p-type wafers (e^-)



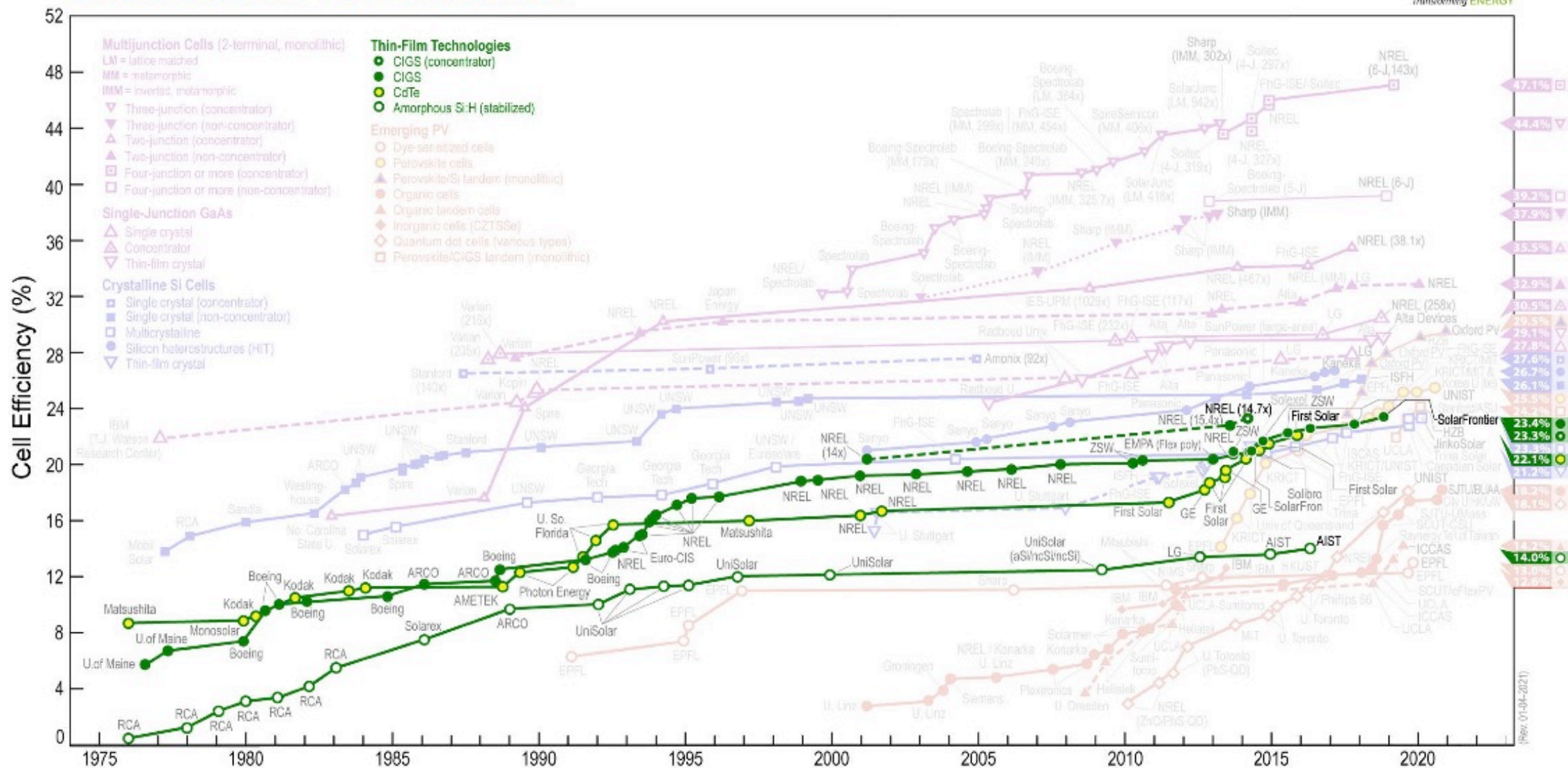
Best Research-Cell Efficiencies

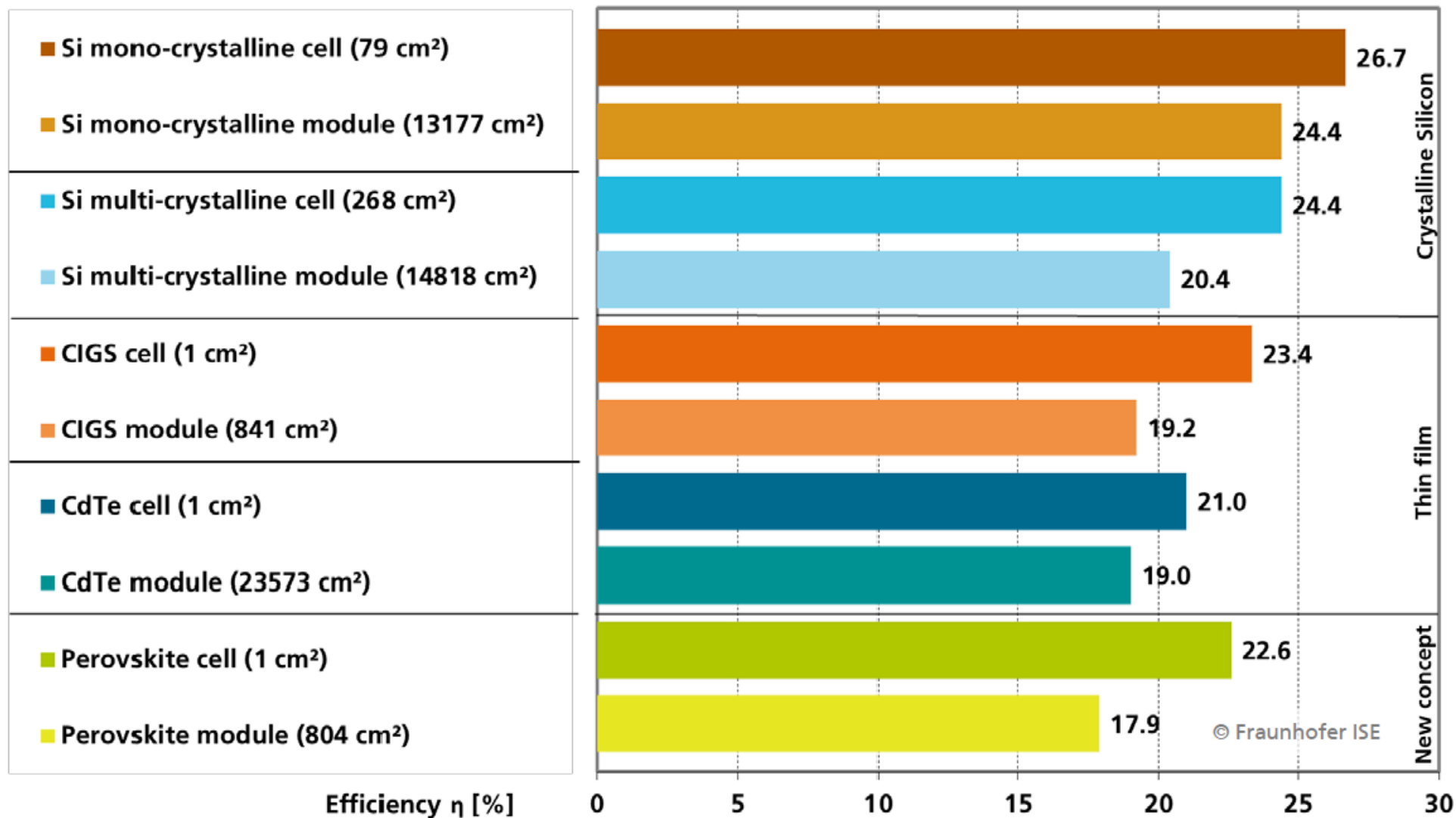


Best Research-Cell Efficiencies



Best Research-Cell Efficiencies





Slides from Fraunhofer Institute, ISE, prepared by Dr. Simon Philipps and Werner Warmuth